

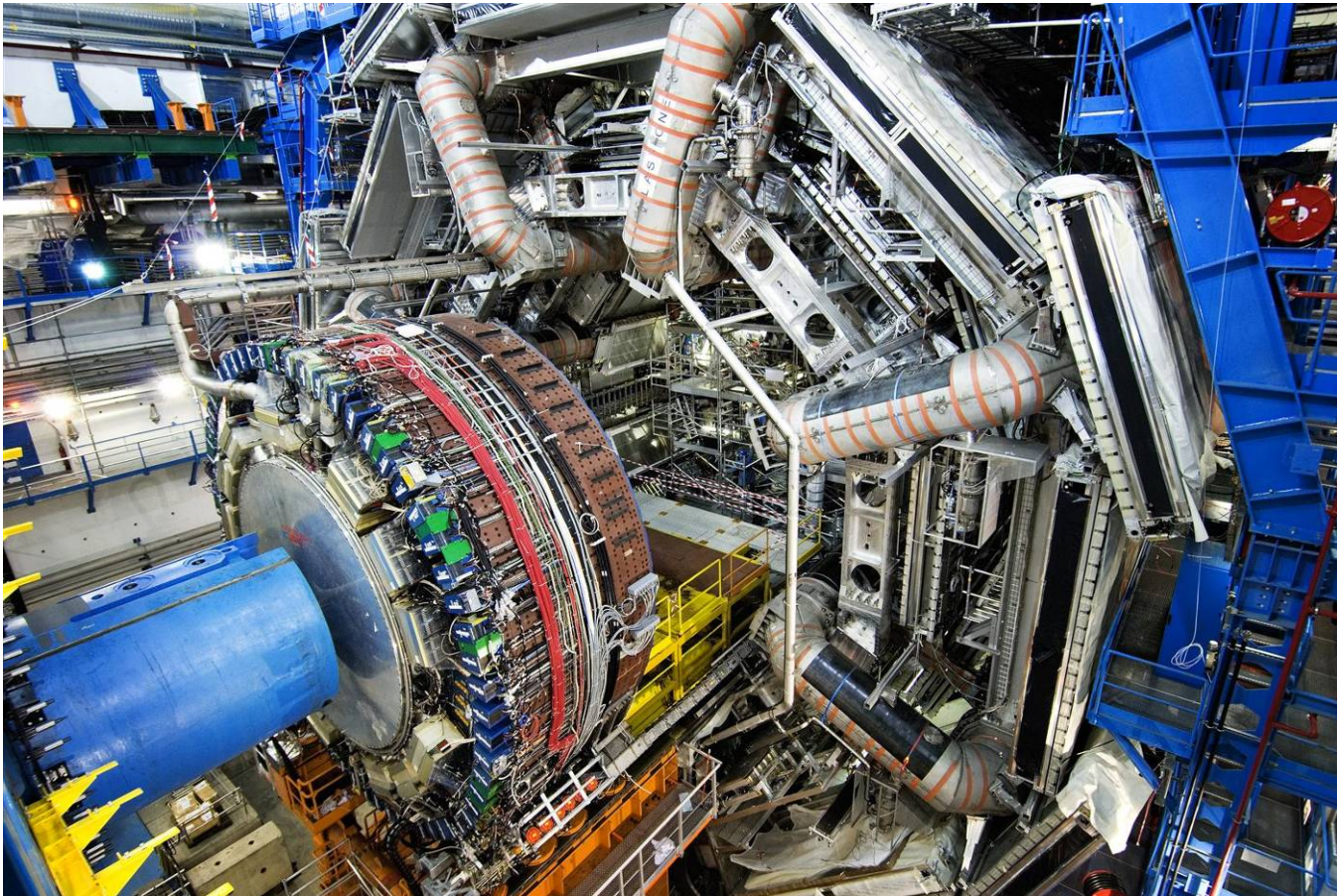
Electronics in particle physics

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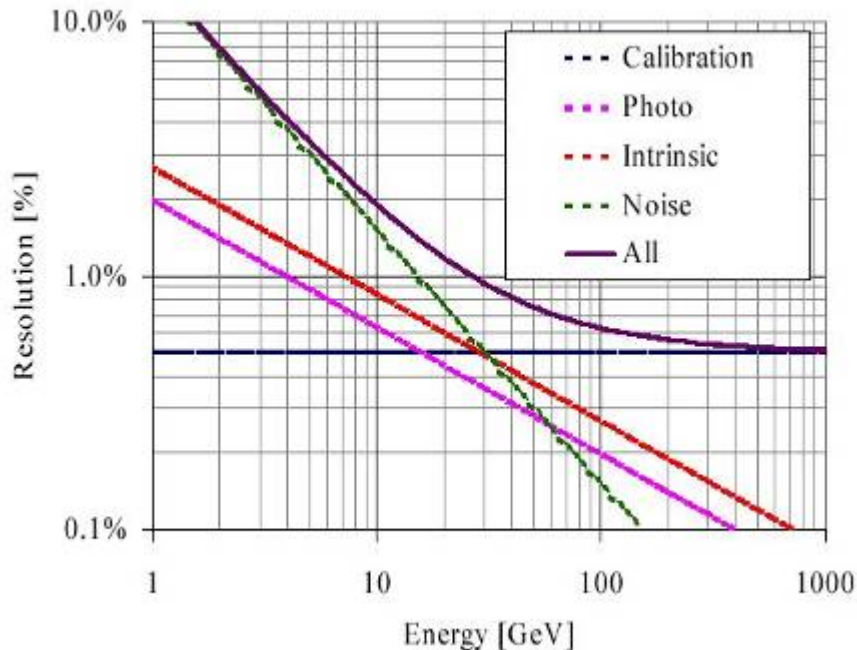
Electronics in experiments

- A lot of electronics in the experiments...
 - Readout electronics : amplification, filtering... : Analog electronics (A,V,C)
 - Processing & Trigger electronics : Digital electronics (bits)
 - The performance of electronics often impacts on the detectors

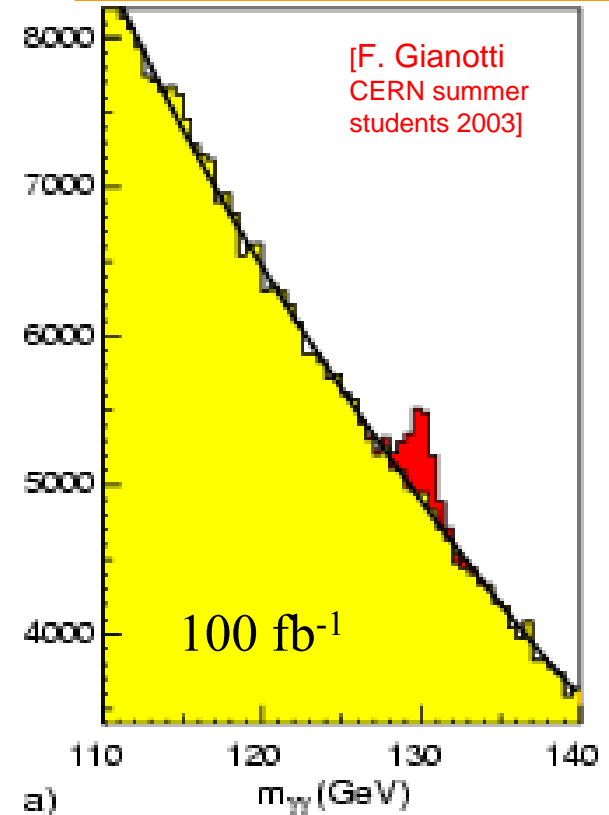


Importance of electronics : calorimeters

- **Calorimetry = energy measurement** (\approx mass)
- **Dynamic range** : maximum signal/minimum signal (or noise)
 - Typically : $10^3 - 10^5$
 - Often specified in dB ($=20\log V_{\max}/V_{\min}$) = 60 - 100 dB
 - Also in bits : $2^n = V_{\max}/v_{\min} = 10 - 18$ bits
- **Precision $\sim 1\%$**
 - Energy resolution : $\sigma(E)$
 - Importance of low noise, uniformity, linearity...

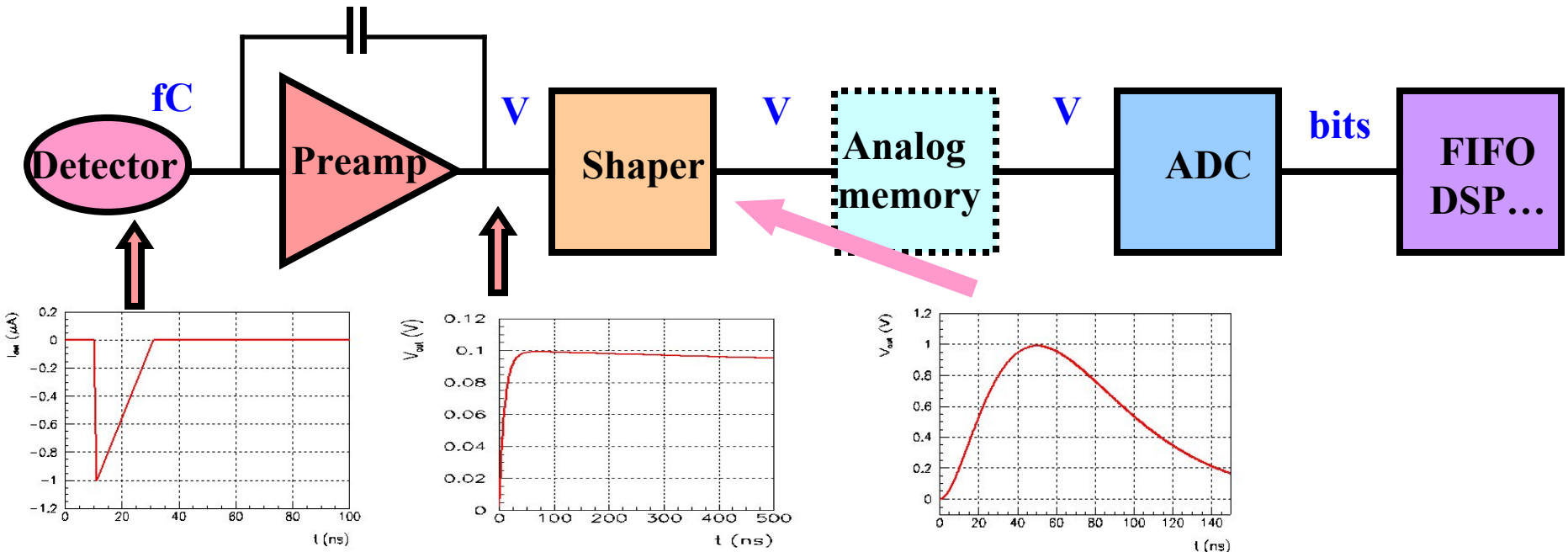


H \rightarrow $\gamma\gamma$ in CMS calorimeter



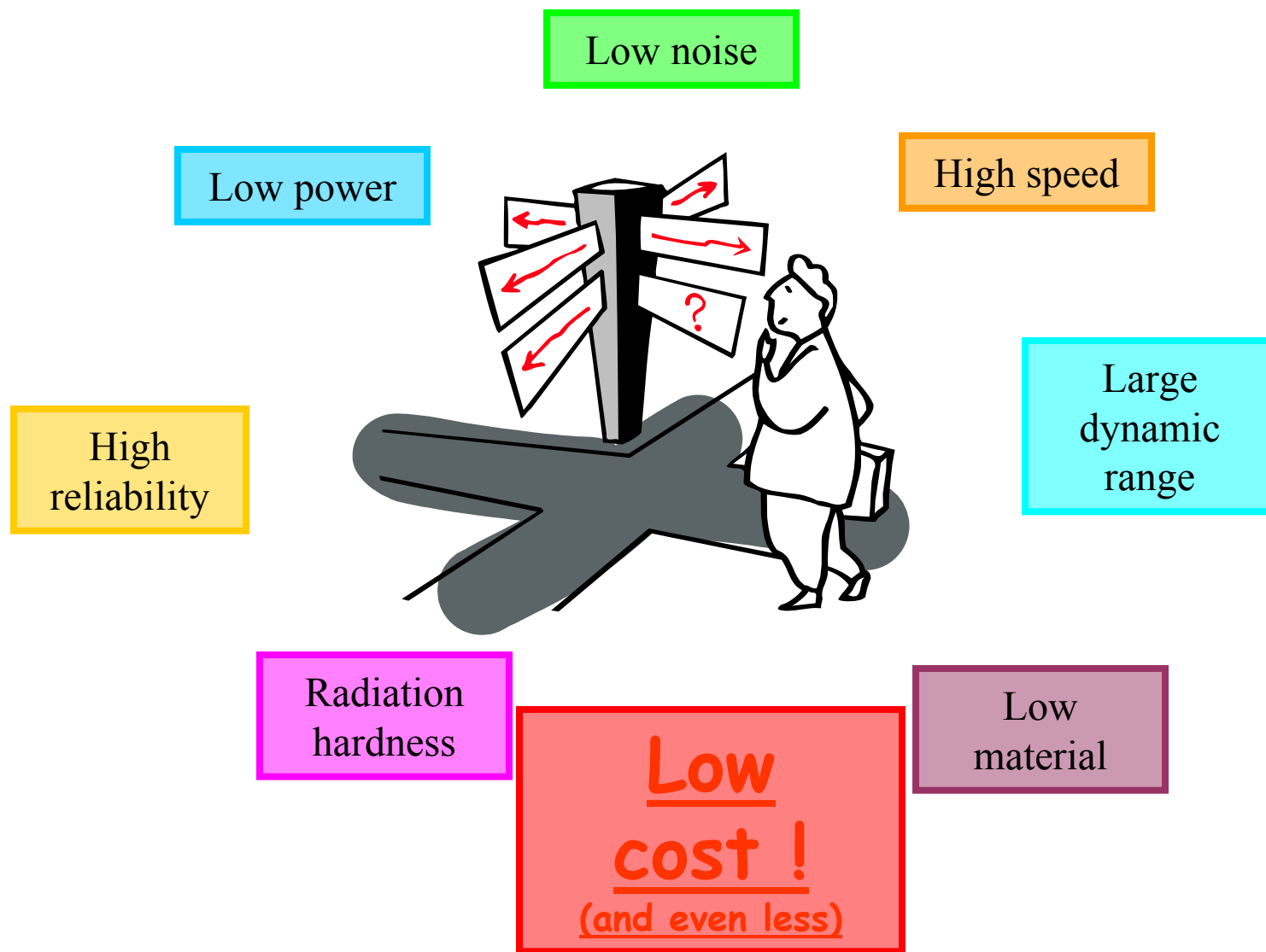
Overview of readout electronics

- Most front-ends follow a similar architecture



- Very small signals (fC) -> need **amplification**
- Measurement of **amplitude** and/or **time** (**ADCs**, **discris**, **TDCs**)
- Several thousands to millions of channels

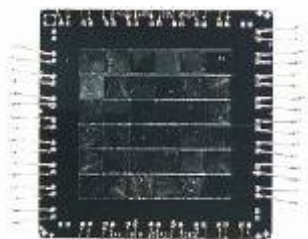
Readout electronics : requirements



Detector(s)

- A large variety
- A similar modelization

PMT for Antares



6x6 pixels, 4x4 mm²
HgTe absorbers, 65 mK
12 eV @ 6 keV

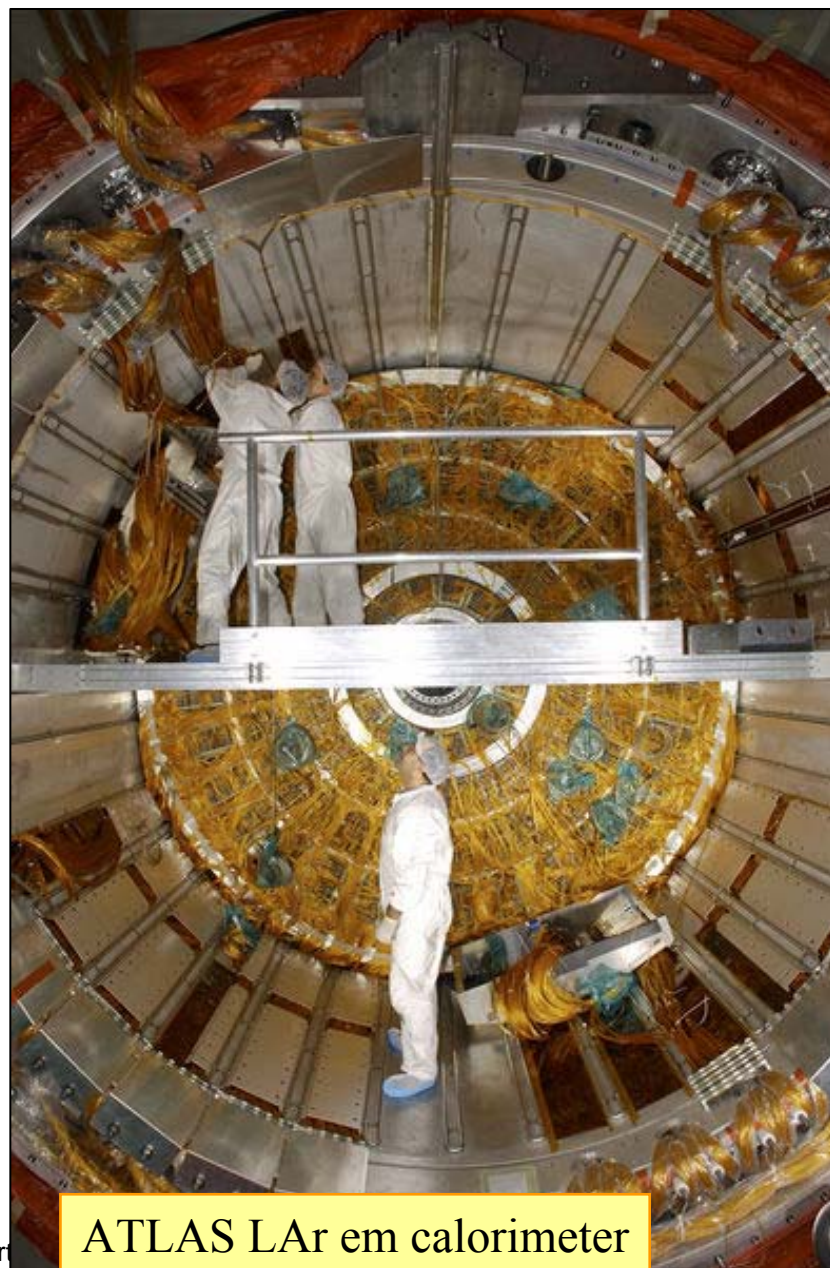
CMS Pixel module



sept 2008

C. de La Taille

Electronics in part



ATLAS LAr em calorimeter

Detector modelization

■ Detector = capacitance C_d

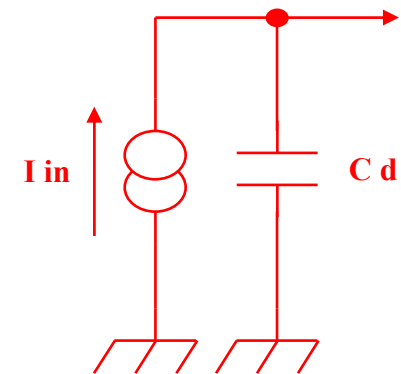
- Pixels : 0.1-10 pF
- PMs : 3-30pF
- Ionization chambers 10-1000 pF
- Capa or transmission line?

■ Signal : current source

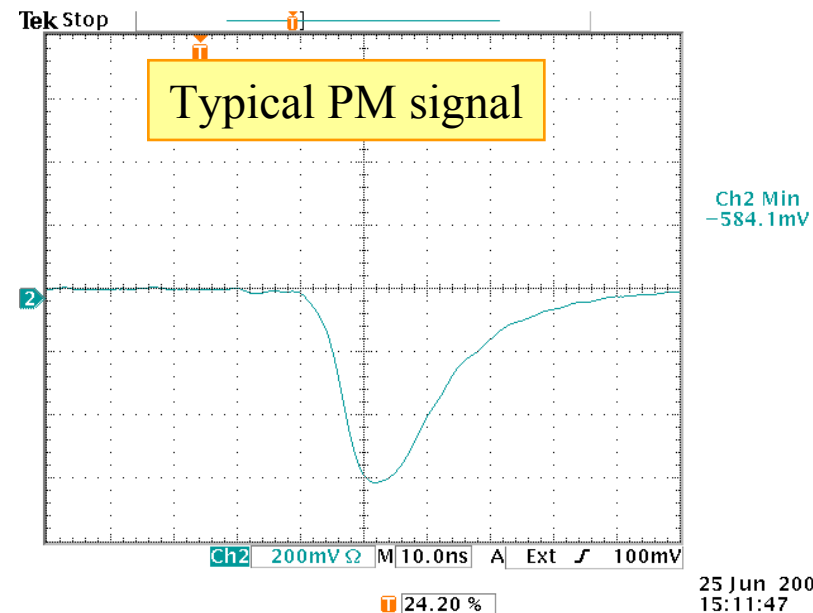
- Pixels : $\sim 100e^-/\mu m$
- PMs : 1 photoelectron $\rightarrow 10^5-10^7 e^-$
- Modelized as an impulse (Dirac) :
 $i(t) = Q_0 \delta(t)$

■ Missing :

- High Voltage bias
- Connections, grounding
- Neighbours
- Calibration...



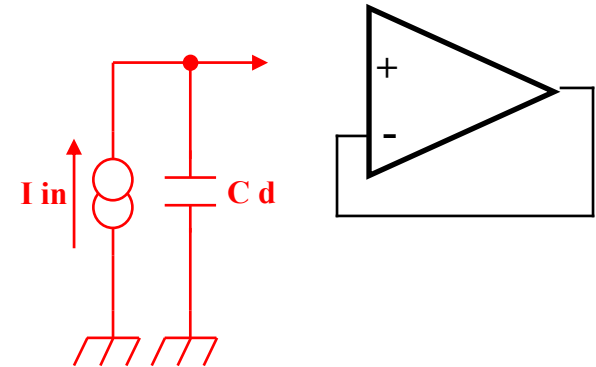
Detector modelisation



Reading the signal

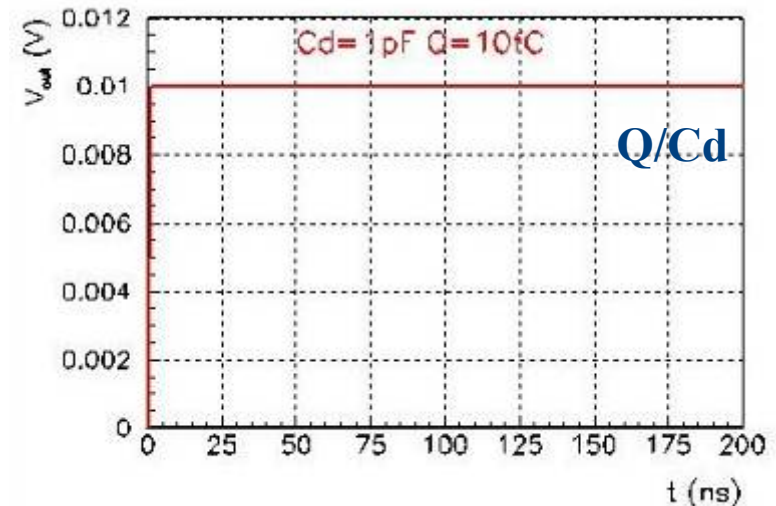
■ Signal

- Signal = current source
- Detector = capacitance C_d
- Quantity to measure
 - Charge => integrator needed
 - Time => discriminator + TDC



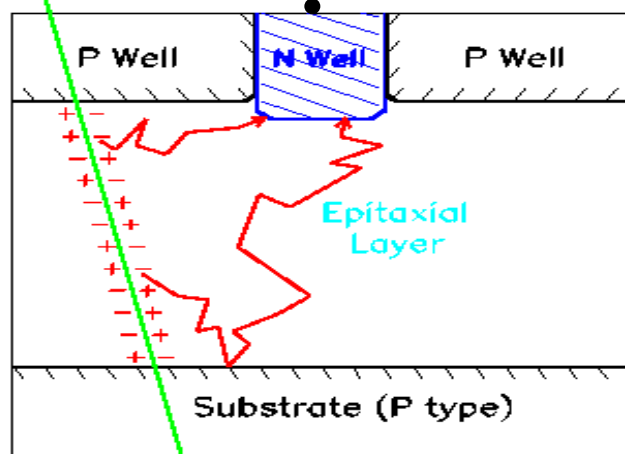
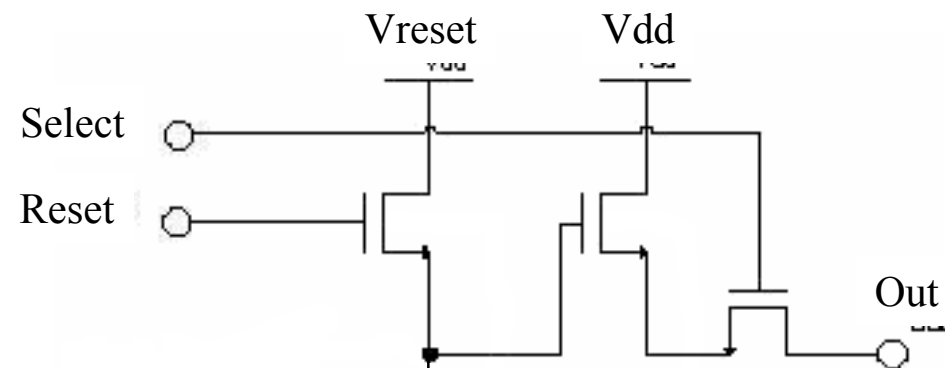
■ Integrating on C_d

- Simple : $V = Q/C_d$
- « Gain » : $1/C_d$: 1 pF -> 1 mV/fC
- Need a follower to buffer the voltage...
- Input follower capacitance : $C_a // C_d$
- Gain loss, possible non-linearities
- crosstalk
- Need to empty C_d ...



Impulse response

Monolithic active pixels



MAPS readout

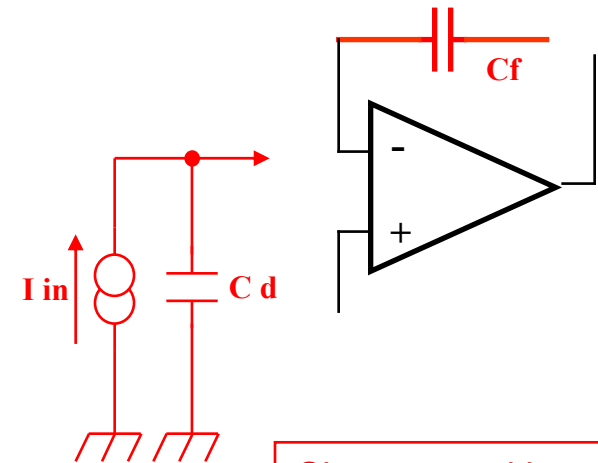
Ideal charge preamplifier

■ ideal opamp in transimpedance

- Shunt-shunt feedback
- transimpedance : v_{out}/i_{in}
- $V_{in}=0 \Rightarrow V_{out}(\omega)/i_{in}(\omega) = -Z_f = -1/j\omega C_f$
- **Integrator** : $v_{out}(t) = -1/C_f \int i_{in}(t)dt$

$$v_{out}(t) = -Q/C_f$$

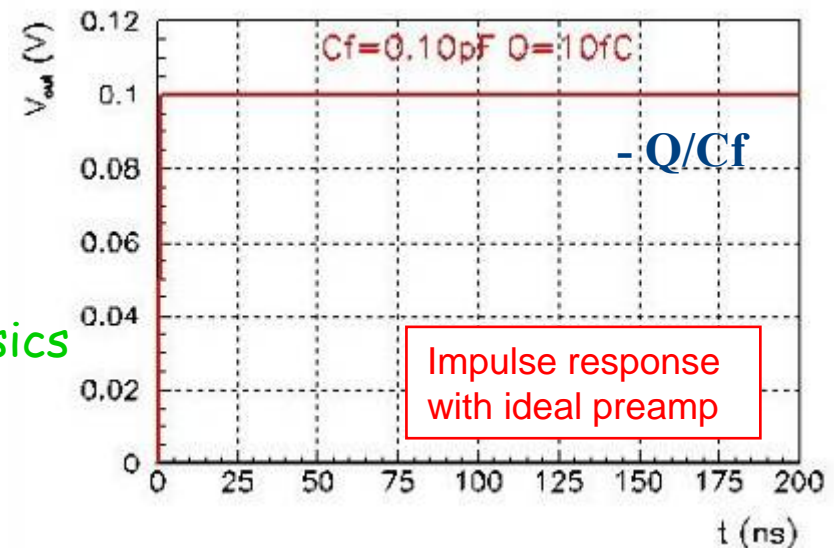
- « Gain » : $1/C_f$: 0.1 pF \rightarrow 10 mV/fC
- C_f determined by maximum signal



Charge sensitive preamp

■ Integration on C_f

- Simple : $V = -Q/C_f$
- Unensitive to preamp capacitance C_{PA}
- Turns a short signal into a long one
- **The front-end of 90% of particle physics detectors...**
- **But always built with custom circuits...**



Non-ideal charge preamplifier

Finite opamp gain

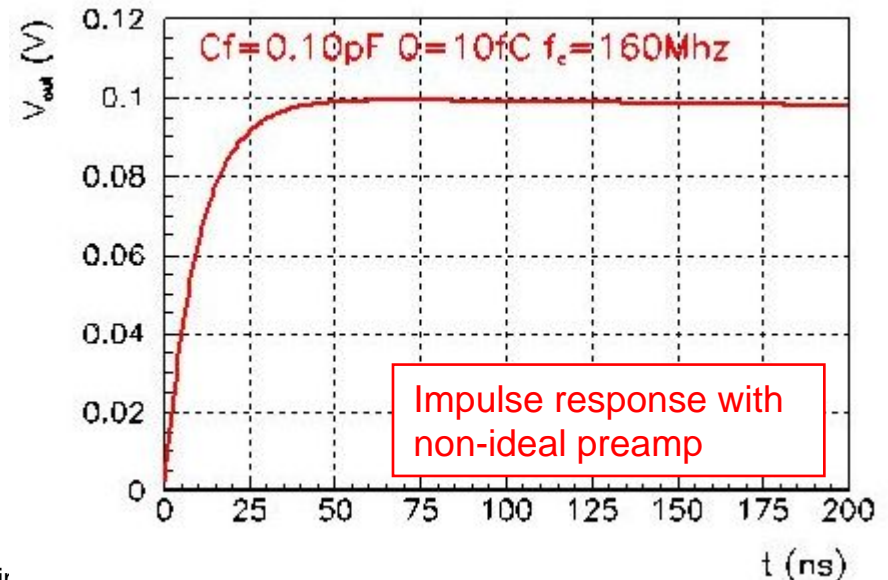
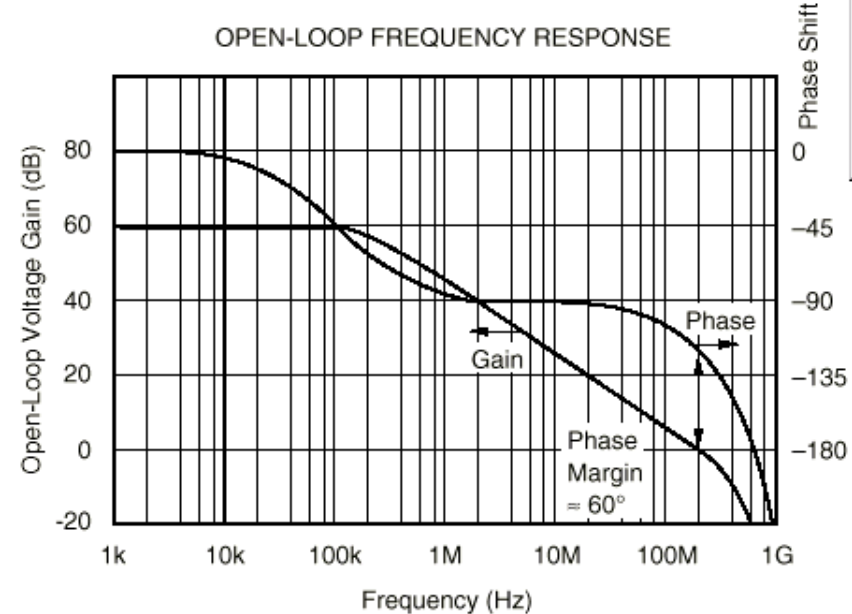
- $V_{out}(w)/i_{in}(w) = -Z_f / (1 + C_d / G_0 C_f)$
- Small signal loss in $C_d / G_0 C_f \ll 1$ (ballistic deficit)

Finite opamp bandwidth

- First order open-loop gain
- $G(w) = G_0 / (1 + j w / w_0)$
 - G_0 : low frequency gain
 - $G_0 w_0$: gain bandwidth product

Preamp risetime

- Due to gain variation with w
- Time constant : τ (tau) = $C_d / G_0 w_0 C_f$
- Rise-time : $t_{10-90\%} = 2.2 \tau$
- Rise-time optimised with $w_{C_{or}} C_f$



Charge preamp seen from the input

Input impedance with ideal opamp

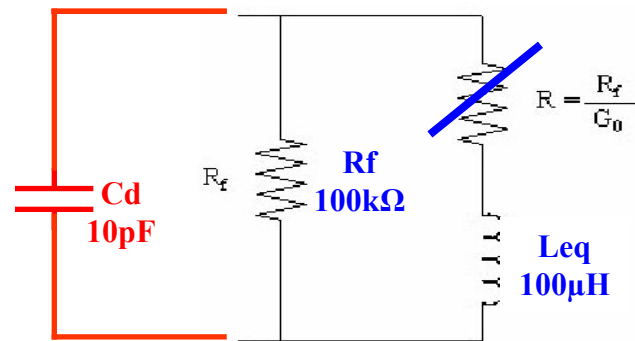
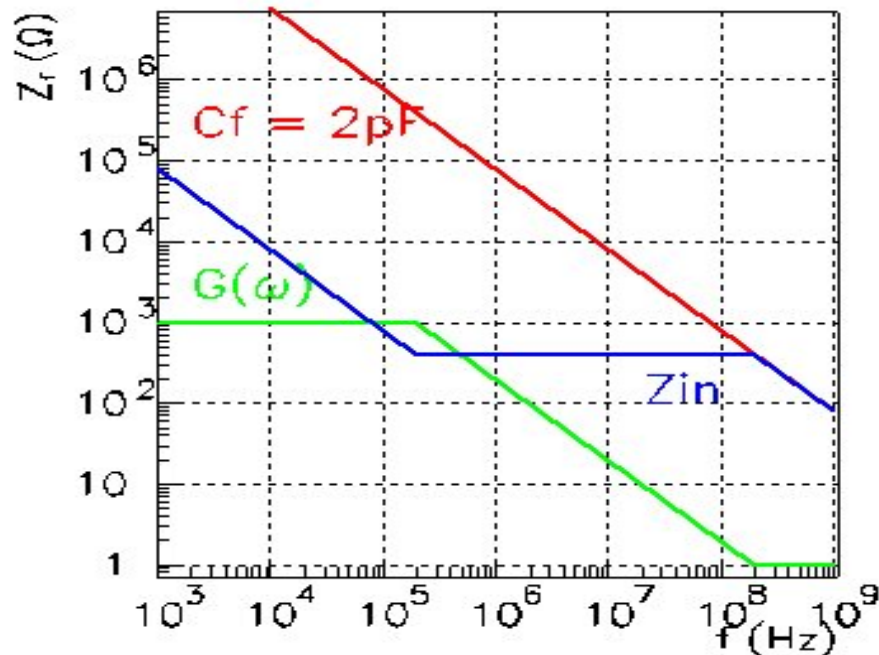
- $Z_{in} = Z_f / G+1$
- $Z_{in} \rightarrow 0$ for ideal opamp
- « Virtual ground » : $V_{in} = 0$
- Minimizes sensitivity to detector impedance
- Minimizes crosstalk

Input impedance with real opamp

- $Z_{in} = 1/j\omega G_0 C_f + 1/G_0 \omega_0 C_f$
- Resistive term : $R_{in} = 1/G_0 \omega_0 C_f$
 - Exemple : $\omega_c = 10^9$ rad/s $C_f = 0.1$ pF \Rightarrow $R_{in} = 10$ k
- Determines the input time constant :
 $\tau = R_{eq} C_d$
- Good stability = (...!)

Equivalent circuit :

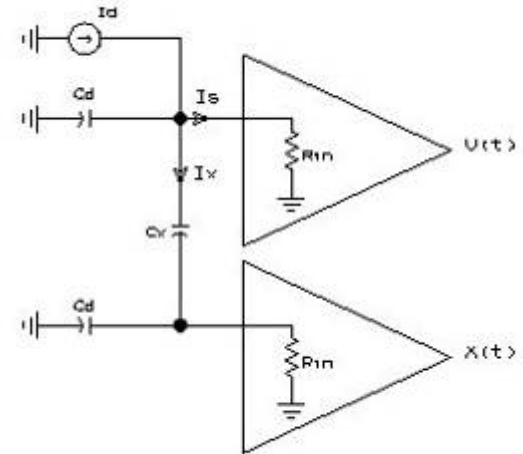
Input impedance or charge preamp



Crosstalk

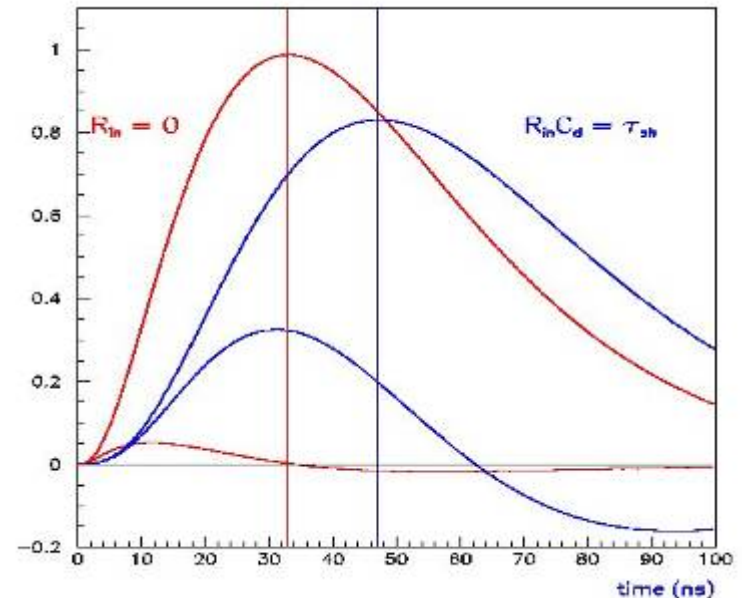
■ Capacitive coupling between neighbours

- Crosstalk signal is **differentiated and with same polarity**
- Small contribution at signal peak
- Proportional to C_x/C_d and preamp input impedance
- Slowed derivative if $R_{in}C_d \sim t_p \Rightarrow$ non-zero at peak



■ Inductive coupling

- Inductive common ground return
- "Ground apertures" = inductance
- Connectors : mutual inductance



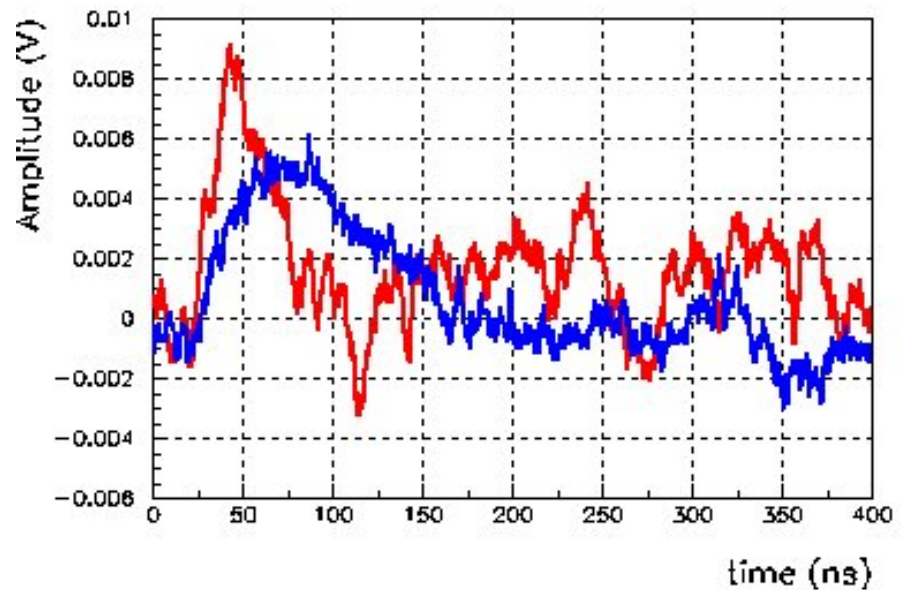
Electronics noise

■ Definition of Noise

- Random fluctuation superposed to interesting signal
- Statistical treatment

■ Three types of noise

- Fundamental noise (Thermal noise, shot noise)
- Excess noise ($1/f$...)
- Parasitics -> EMC/EMI (pickup noise, ground loops...)



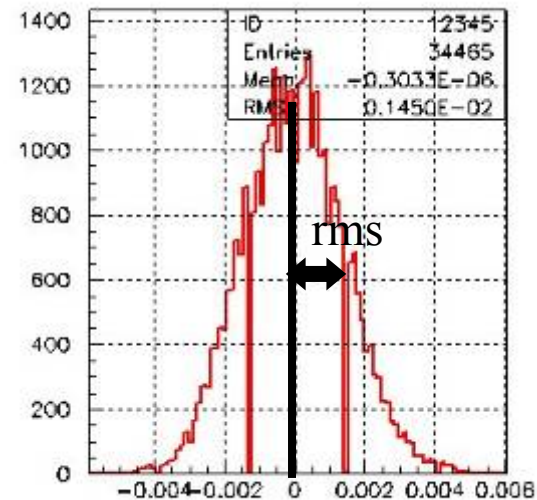
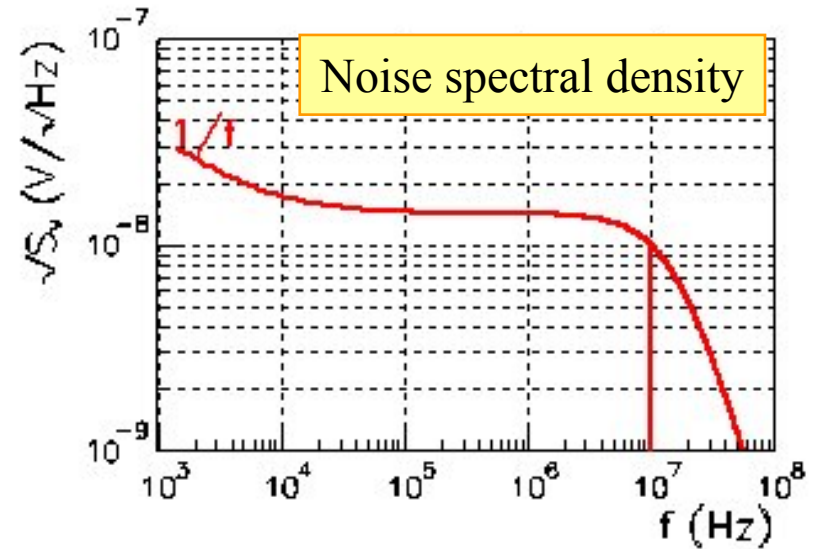
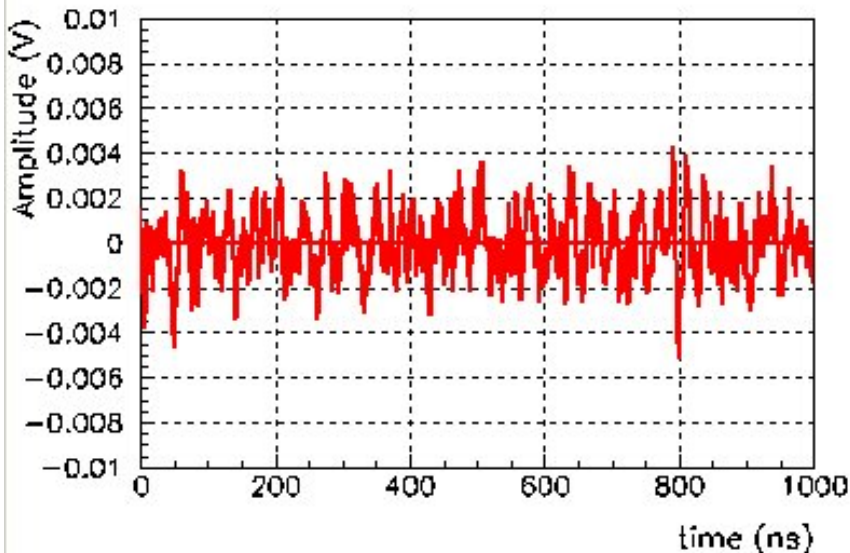
Electronics noise

Modelization

- Noise generators : e_n, i_n ,
- Noise spectral density of e_n & i_n : $S_v(f)$ & $S_i(f)$
- $S_v(f) = |F(e_n)|^2$ (V^2/Hz)

Rms noise V_n

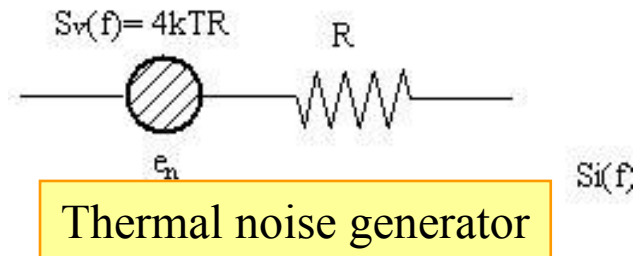
- $V_n^2 = \int e_n^2(t) dt = \int S_v(f) df$
- White noise (e_n) : $V_n = e_n \sqrt{\frac{1}{2}\pi f_{-3dB}}$



Calculating electronics noise

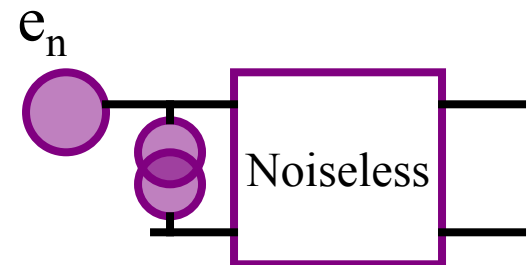
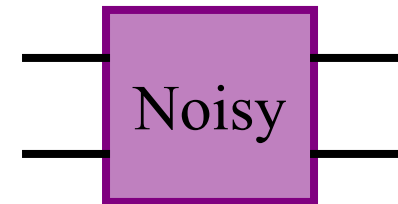
■ Fundamental noise

- Thermal noise (**resistors**): $S_v(f) = 4kTR$
- Shot noise (**junctions**): $S_i(f) = 2qI$



■ Noise referred to the input

- All noise generators can be referred to the input as **2** noise generators :
- A voltage one e_n in series : **series noise**
- A current one i_n in parallel : **parallel noise**
- Two generators : no more, no less... why ?
 - **To take into account the Source impedance**



■ Golden rule

- **Always calculate the signal before the noise**
what counts is the signal to noise ratio
- Don't forget noise generators are $V^2/Hz \Rightarrow$ calculations in module square
- Practical exercice next slide

Noise generators referred to the input

Noise in charge pre-amplifiers

- 2 noise generators at the input

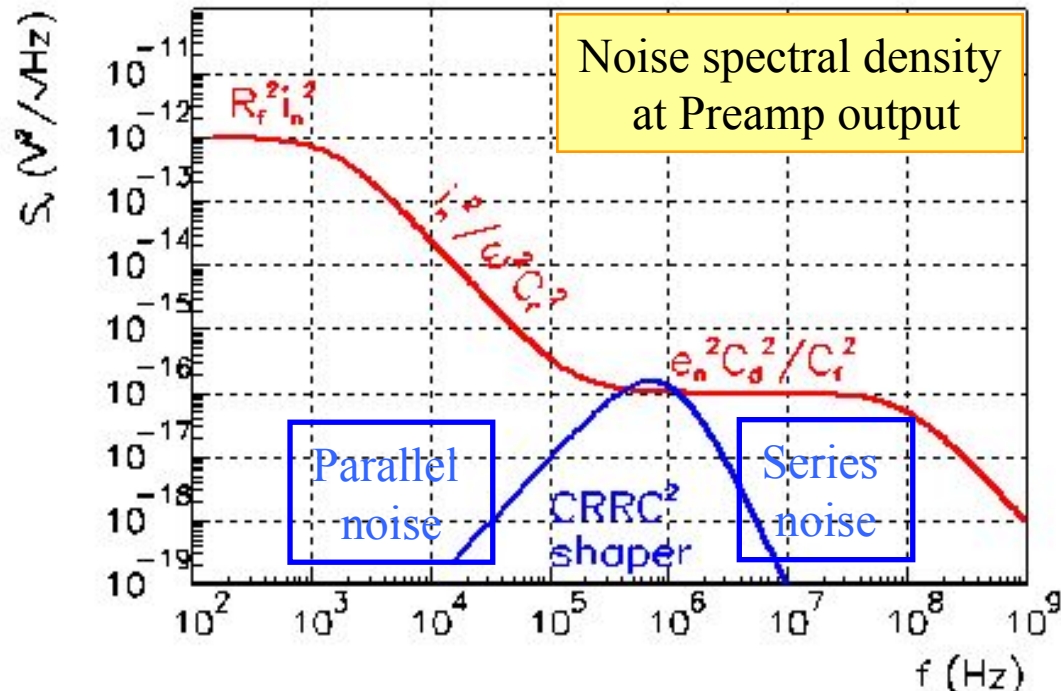
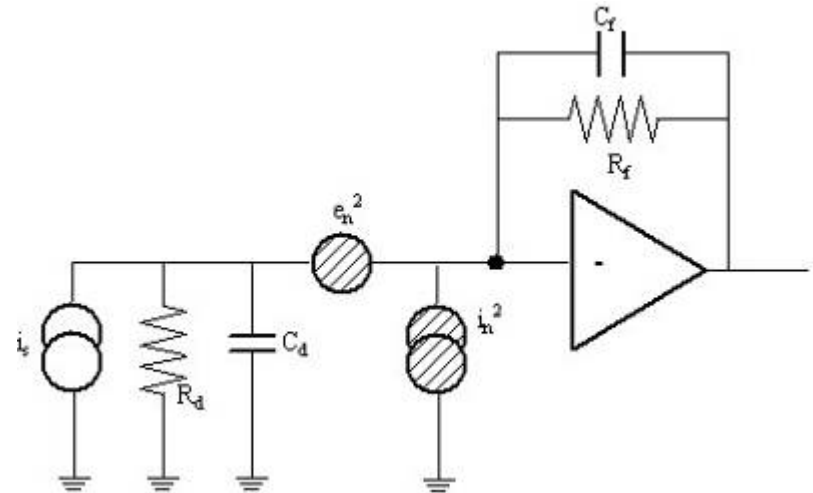
- Parallel noise : (i_n^2) (leakage currents)
- Series noise : (e_n^2) (preamp)

- Output noise spectral density :

- $S_v(\omega) = (i_n^2 + e_n^2/|Z_d|^2) / \omega^2 C_f^2$
 $= i_n^2 / \omega^2 C_f^2 + e_n^2 C_d^2 / C_f^2$
- Parallel noise in $1/\omega^2$
- Series noise is flat, with a « noise gain » of C_d/C_f

- rms noise V_n

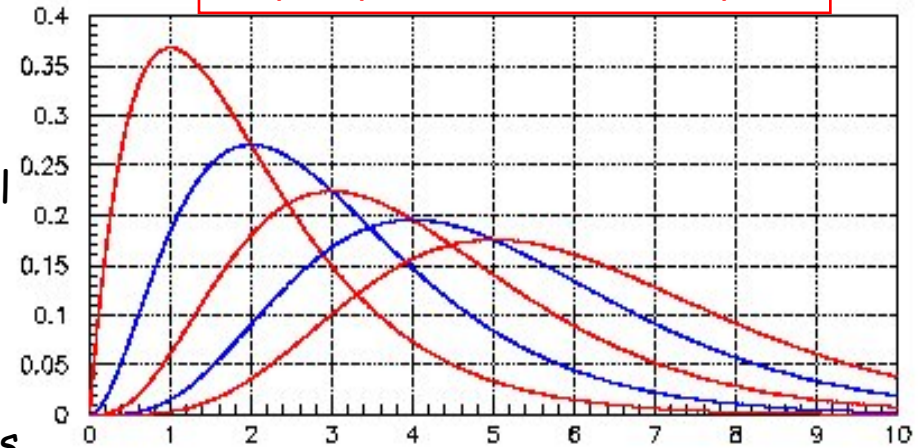
- $V_n^2 = \int S_v(\omega) d\omega / 2\pi \rightarrow \infty$ (!)
- Benefit of shaping...



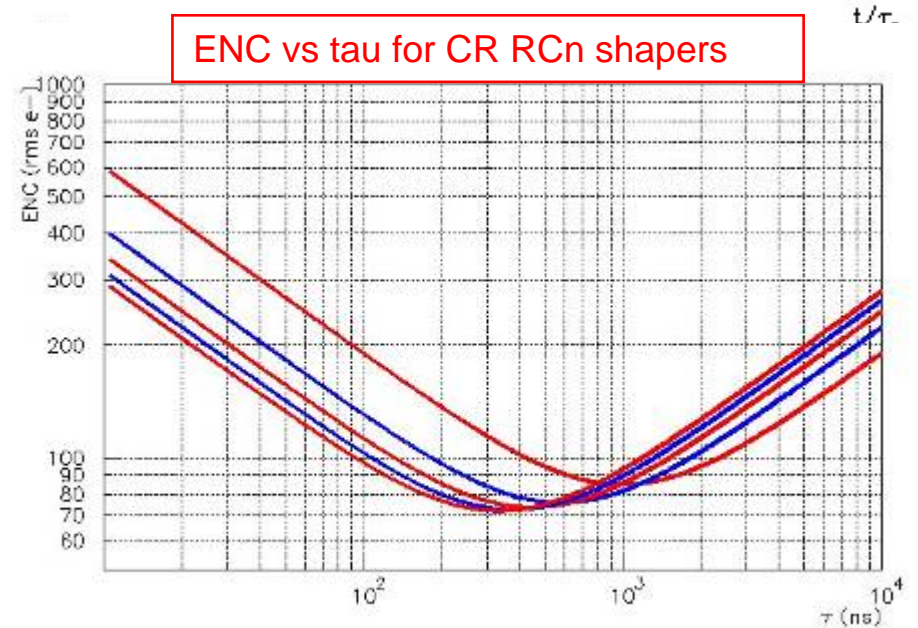
Equivalent Noise Charge (ENC) after CRRCⁿ

- Noise reduction by optimising useful bandwidth
 - Low-pass filters (RCⁿ) to cut-off high frequency noise
 - High-pass filter (CR) to cut-off parallel noise
 - -> pass-band filter CRRCⁿ
- Equivalent Noise Charge : ENC
 - Noise referred to the input in electrons
 - $ENC = I_a(n) e_n C_T / \sqrt{\tau} \oplus I_b(n) i_n^* \sqrt{\tau}$
 - Series noise in $1/\sqrt{\tau}$
 - Parallel noise in $\sqrt{\tau}$
 - 1/f noise independant of τ
 - Optimum shaping time $\tau_{opt} = \tau_c / \sqrt{2n-1}$
- Peaking time tp (5-100%)
 - ENC(tp) independent of n
- Complex shapers are **obsolete** :
 - Power of **digital filtering**
 - Analog filter = CRRC ou CRRC²

Step response of CR RCⁿ shapers



ENC vs tau for CR RCⁿ shapers



Equivalent Noise Charge (ENC) after CRRCⁿ

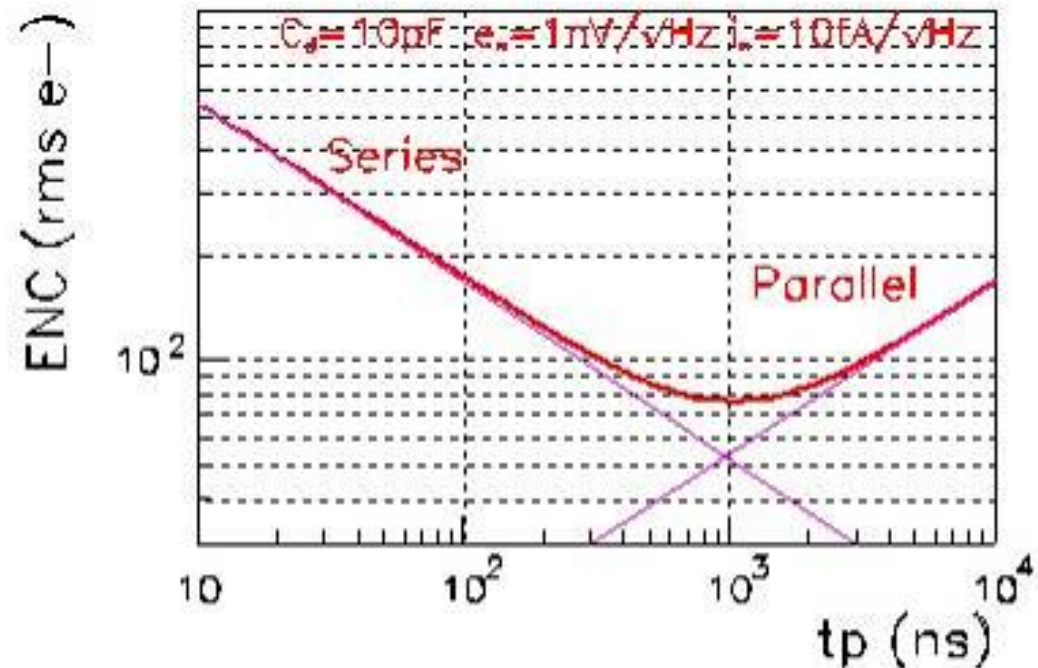
- A useful formula : ENC (e⁻ rms) after a CRRC² shaper :

$$\text{ENC} = 174 e_n C_{\text{tot}} / \sqrt{t_p} (\delta) \oplus 166 i_n \sqrt{t_p} (\delta)$$

- e_n in nV/√Hz, i_n in pA/√Hz are the **preamp** noise spectral densities
- C_{tot} (in pF) is dominated by the detector (C_d) + input preamp capacitance (C_{pA})
- t_p (in ns) is the shaper peaking time (5-100%)

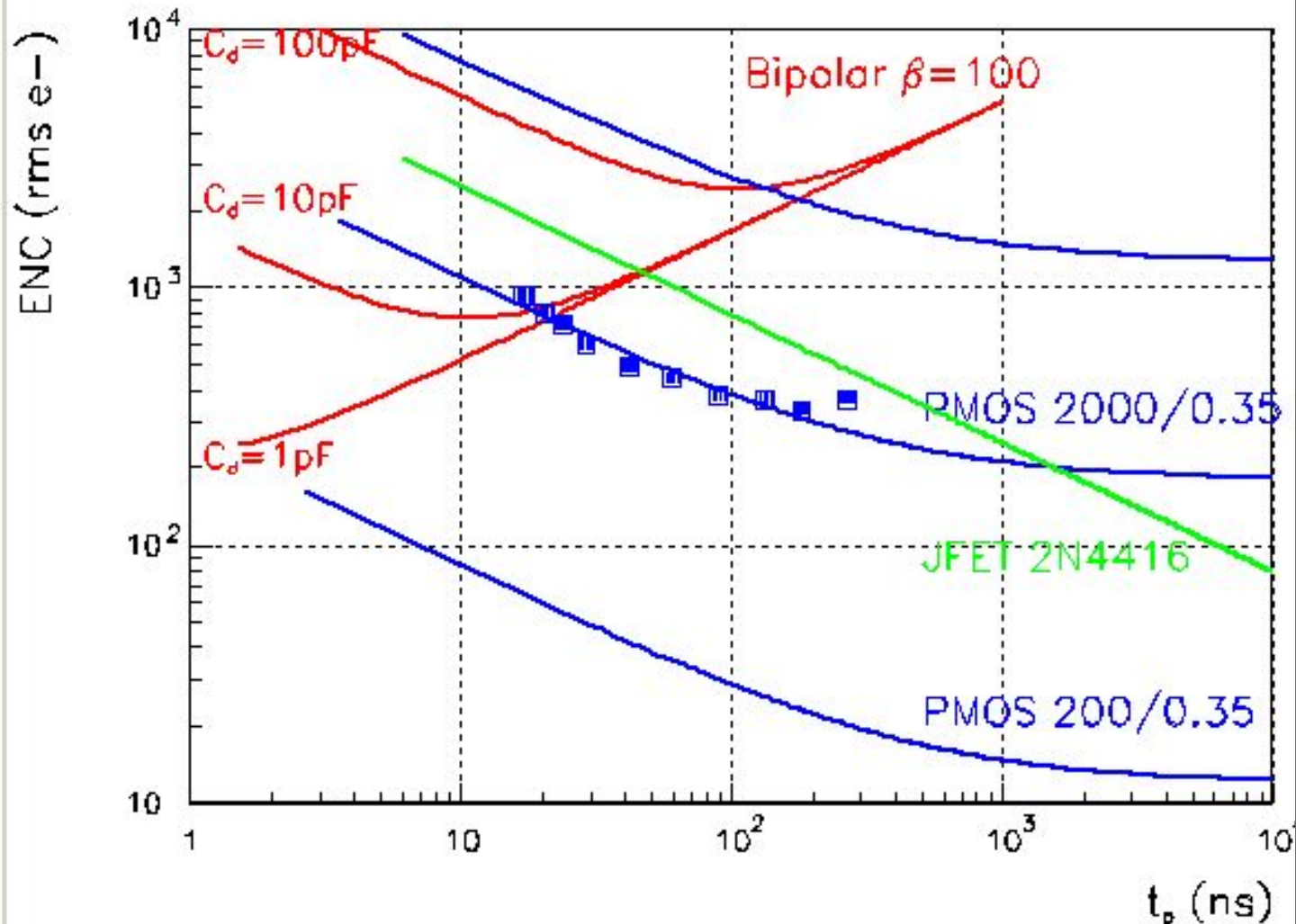
■ Noise minimization

- Minimize source capacitance
- Operate at optimum shaping time
- Preamp series noise (e_n) best with high transconductance (g_m) in input transistor
=> large current, optimal size



ENC for various technologies

- ENC for $C_d=1, 10$ and 100 pF at $I_D = 500$ μ A
 - MOS transistors best between 20 ns - 2 μ s



Parameters

Bipolar :

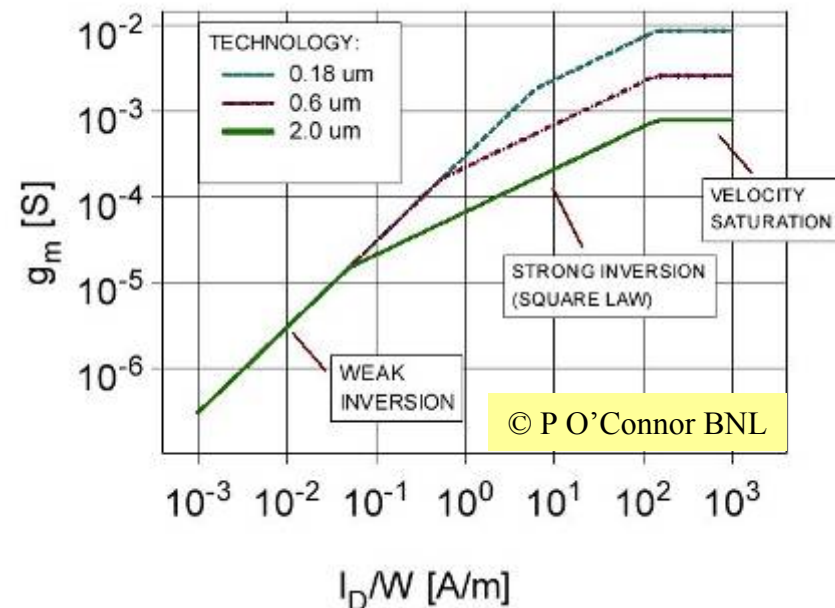
- $g_m = 20$ mA/V
- $R_{BB'} = 25$ Ω
- $e_n = 1$ nV/ \sqrt Hz
- $I_B = 5$ μ A
- $i_n = 1$ pA/ \sqrt Hz
- $C_{PA} = 100$ fF

PMOS 2000/0.35

- $g_m = 10$ mA/V
- $e_n = 1.4$ nV/ \sqrt Hz
- $C_{PA} = 5$ pF
- $1/f$:

MOS input transistor sizing

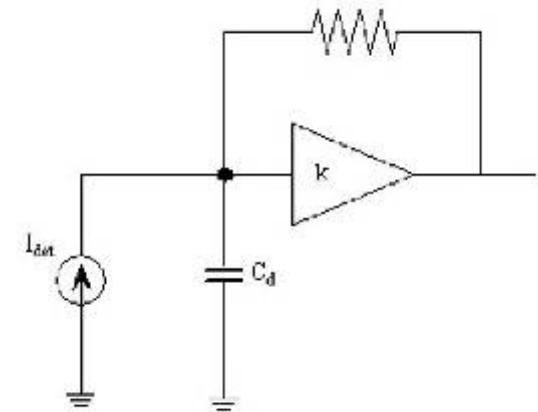
- **Capacitive matching : strong inversion**
 - g_m proportionnal to $W/L \sqrt{I_D}$
 - C_{GS} proportionnal to $W \cdot L$
 - ENC proportionnal to $(C_{det} + C_{GS}) / \sqrt{g_m}$
 - Optimum W/L : $C_{GS} = 1/3 C_{det}$
 - Large transistors are easily in moderate or weak inversion at small current
- **Optimum size in weak inversion**
 - g_m proportionnal to I_D (indep of W, L)
 - ENC minimal for C_{GS} minimal, provided the transistor remains in weak inversion



Current preamplifiers :

■ Transimpedance configuration

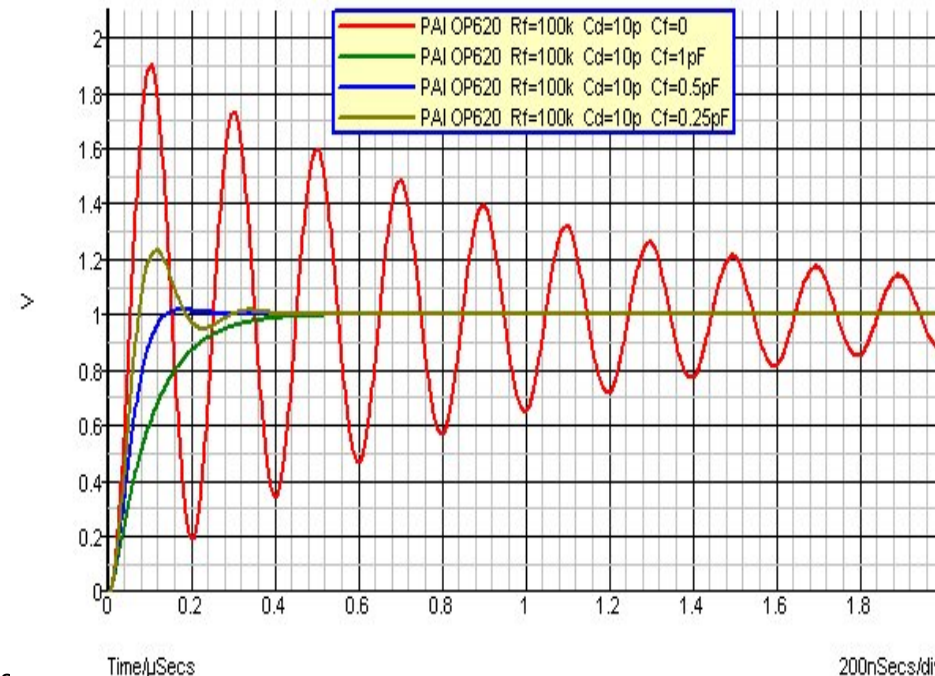
- $V_{out}(\omega)/i_{in}(\omega) = -R_f / (1+Z_f/GZ_d)$
- Gain = R_f
- High counting rate
- Typically optical link receivers



Current sensitive preamp

■ Easily oscillatory

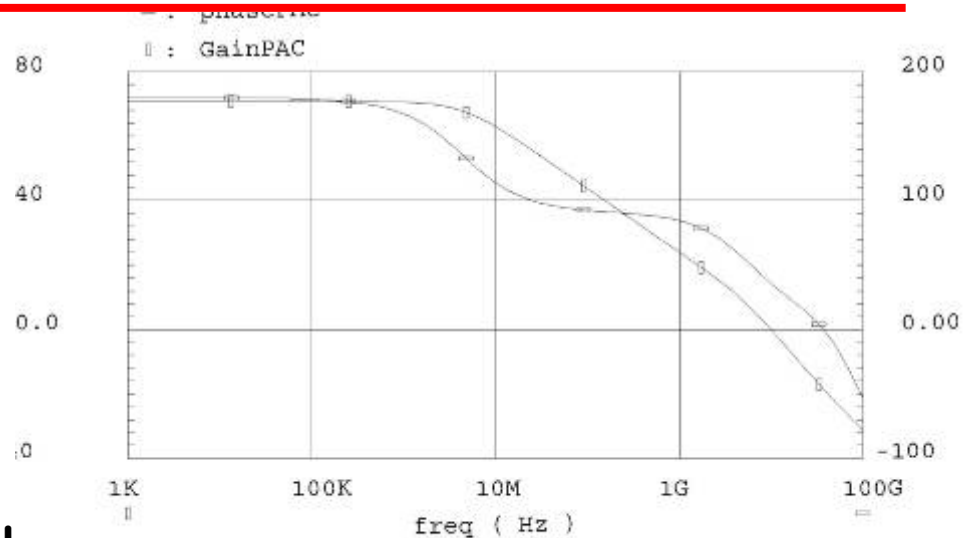
- Unstable with capacitive detector
- Inductive input impedance
 $L_{eq} = R_f / \omega C_d$
- Resonance at : $f_{res} = 1/2\pi \sqrt{L_{eq}C_d}$
- Quality factor : $Q = R / \sqrt{L_{eq}/C_d}$
 - $Q > 1/2 \rightarrow$ ringing
- Damping with capacitance C_f
 - $C_f = 2 \sqrt{C_d/R_f G_0 \omega_0}$
 - Easier with fast amplifiers
 -



High speed transimpedance amplifier

Fast transimpedance amplifiers

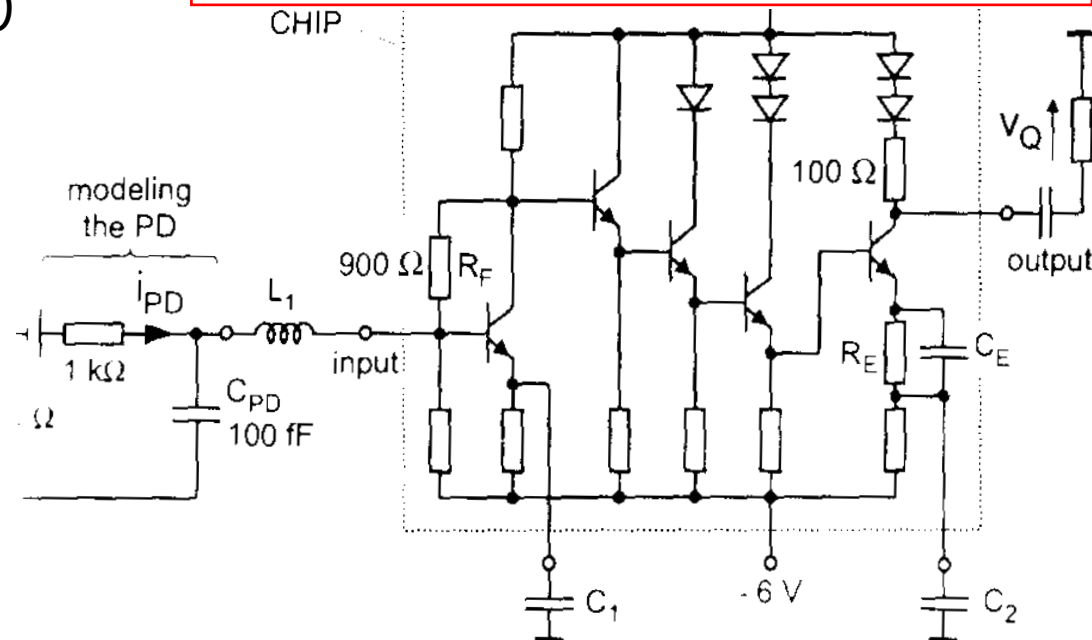
- $R_f = 25k$ $C_f = 10fF$
- SiGe process
- 15 GHz gain-bandwidth product



40 Gb/s transimpedance for optical

- Simple architecture (CE + CC)
- SiGe bipolar transistors
- CC outside feedback loop
- « pole splitting »

Open loop frequency response of SiGe amplifier



Charge vs Current preamps

■ Charge preamps

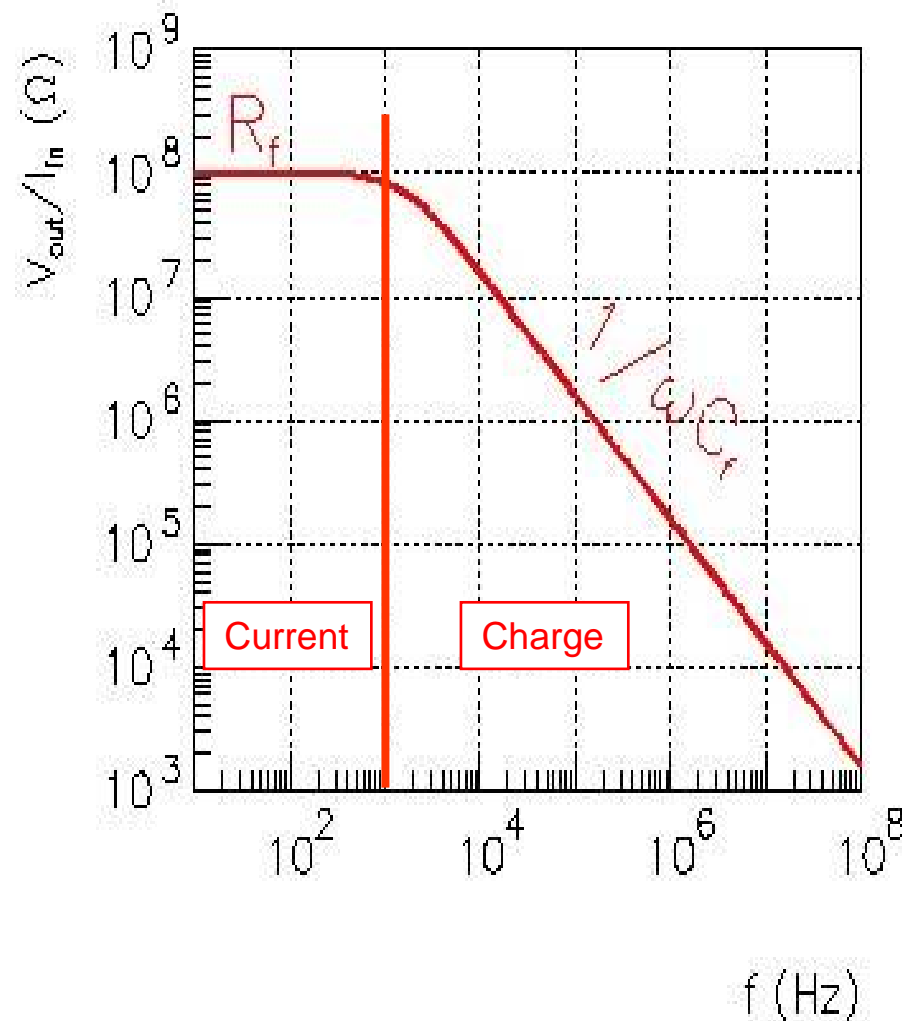
- Best noise performance
- Best with short signals
- Best with small capacitance

■ Current preamps

- Best for long signals
- Best for high counting rate
- Significant parallel noise

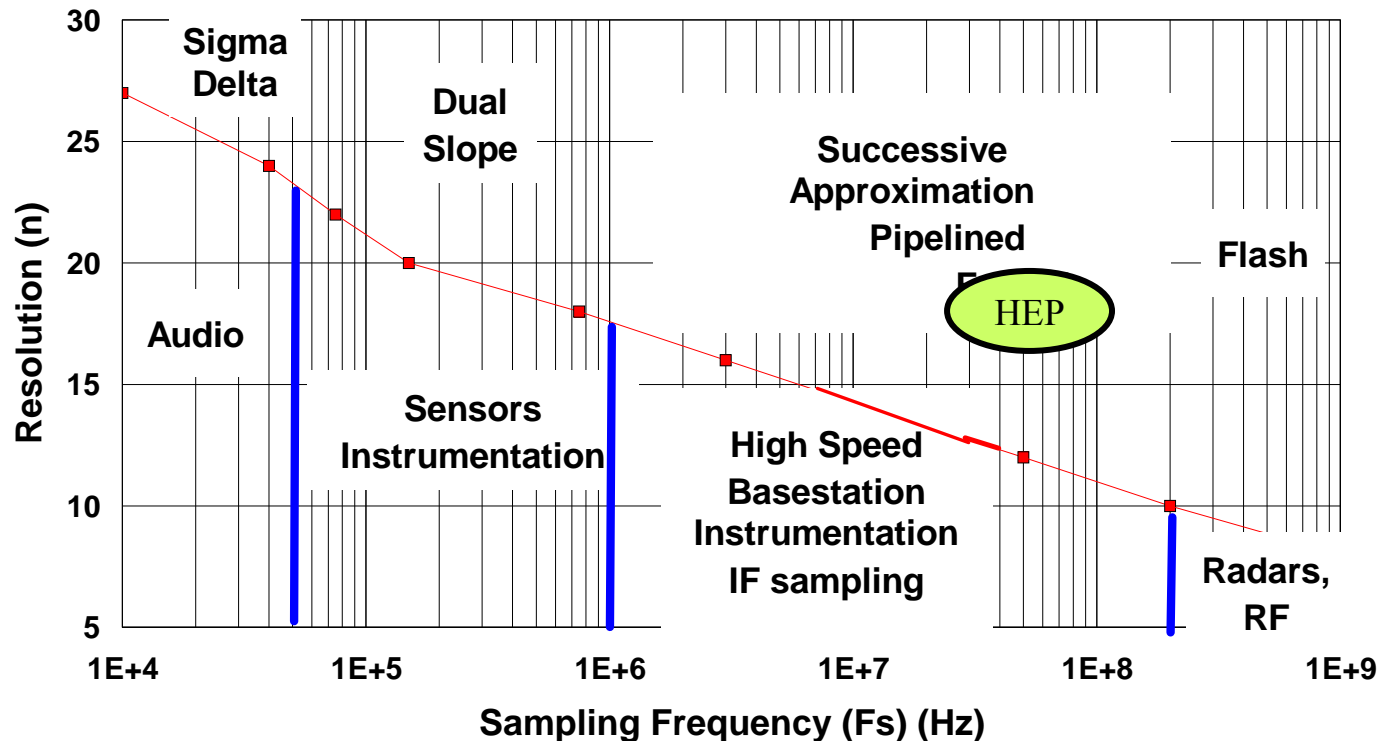
■ Charge preamps are not slow, they are long

■ Current preamps are not faster, they are shorter (but easily unstable)



ADCs : G.D.A.S.A.P.

- The era of G.D.A.S.A.P. : « go digital as soon as possible »
 - Spectacular evolution of ADCs : more bits, faster, less watts
 - Propelled by evolution of technologies and telecom
- Has revolutionnized signal processing
- Now coming inside the ASICs

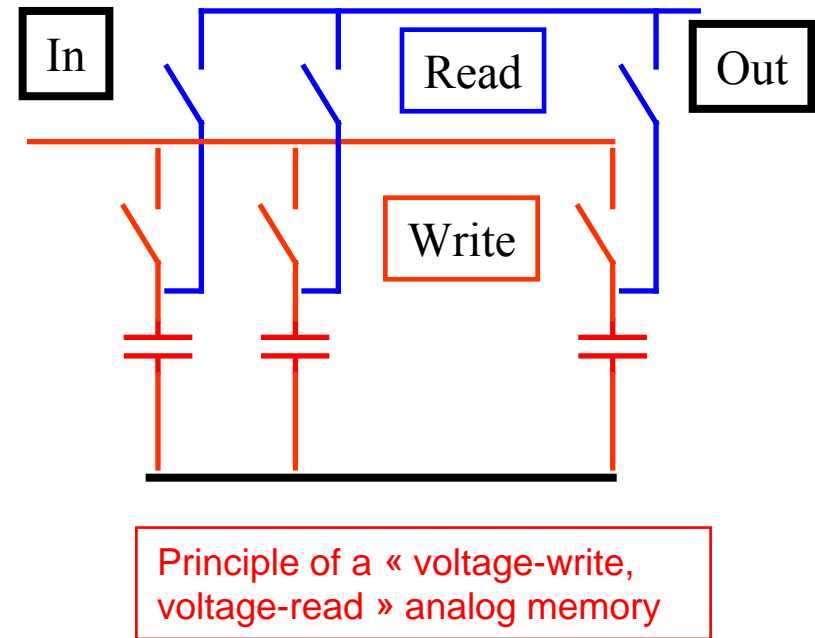


Resolution
vs speed
of ADCs
in 2002

© L. Dugoujon
STm

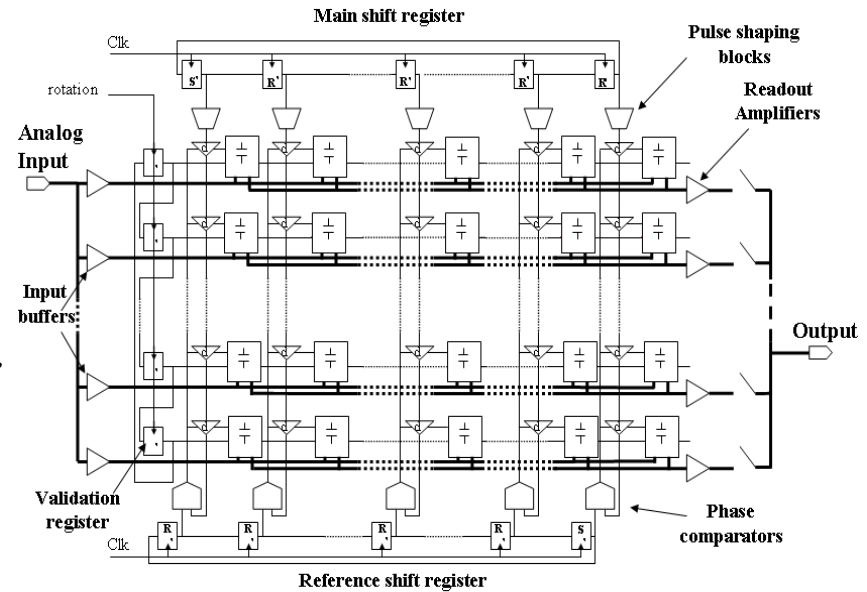
Analog memories

- **Switched Capacitor Arrays (SCAs)**
 - Store signal on capacitors (\sim pF)
 - Fast write (\sim GHz)
 - Slower read (\sim 10MHz)
 - Dynamic range : 10-13 bits
 - depth : 100-2000 caps
 - Unensitive to cap absolute value (voltage write, voltage read)
 - Low power
 - Possible loss in signal integrity (droop, leakage current)
- The base of 90% of digital oscilloscopes !



The MATAcq chip: an oscilloscope on a chip

- Based on the Sampling Matrix principle: evolution of the sampling DLL technique.
- Also includes 10ps precision TAC for trace synchronisation..
- AMS 0.8 μ m technology
- 2560 samples.
- < 1 μ s readout time.
- 50 MS/s-2GS/s range.
- 300 MHz Bandwidth.
- 13.5 bit rms dynamic range
- Jitter < 30 ps rms.



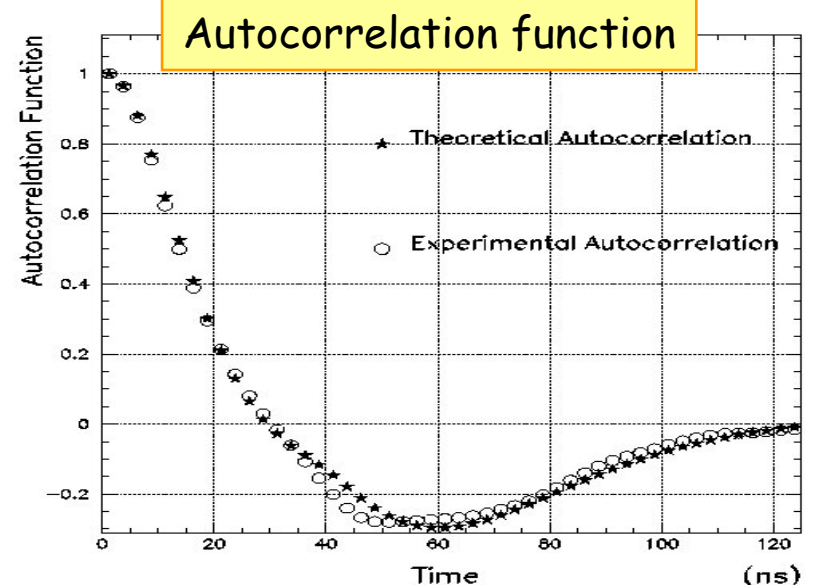
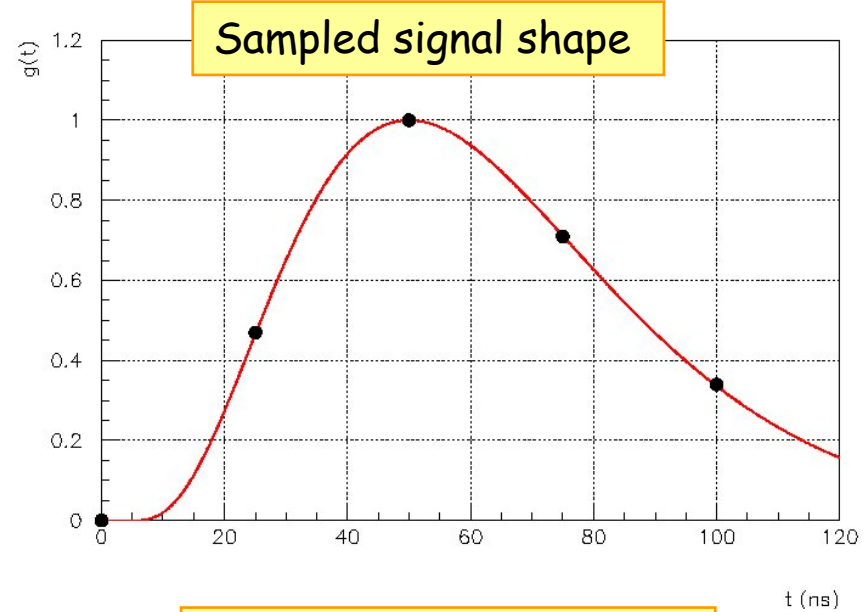
IEEE TNS 52-6:2853-2860,2005

- used in the MATAcq (CAEN V1729) board.
- used to read fast photodetectors in small scale experiments or test benches



Digital filtering

- Linear sums of sampled signal
 - Finite Impulse Response (FIR)
 - made possible by fast ADCs (or analog memories)...
- Signal : $s(t) = Ag(t) + b$
 - A : amplitude
 - G(t) : normalised signal shape
 - B : noise
 - Sampled signal : $s_i = Ag_i + b_i$
- Filter : weighted sum $\sum a_i s_i$
 - $a_i = \sum R^{-1}_{ij} g_j$
 - R = autocorrelation fonction
 - g_i = signal shape
(0, 0.63, 1, 0.8, 0.47)
 - $S = \sum_{i=1}^n a_i s_i$



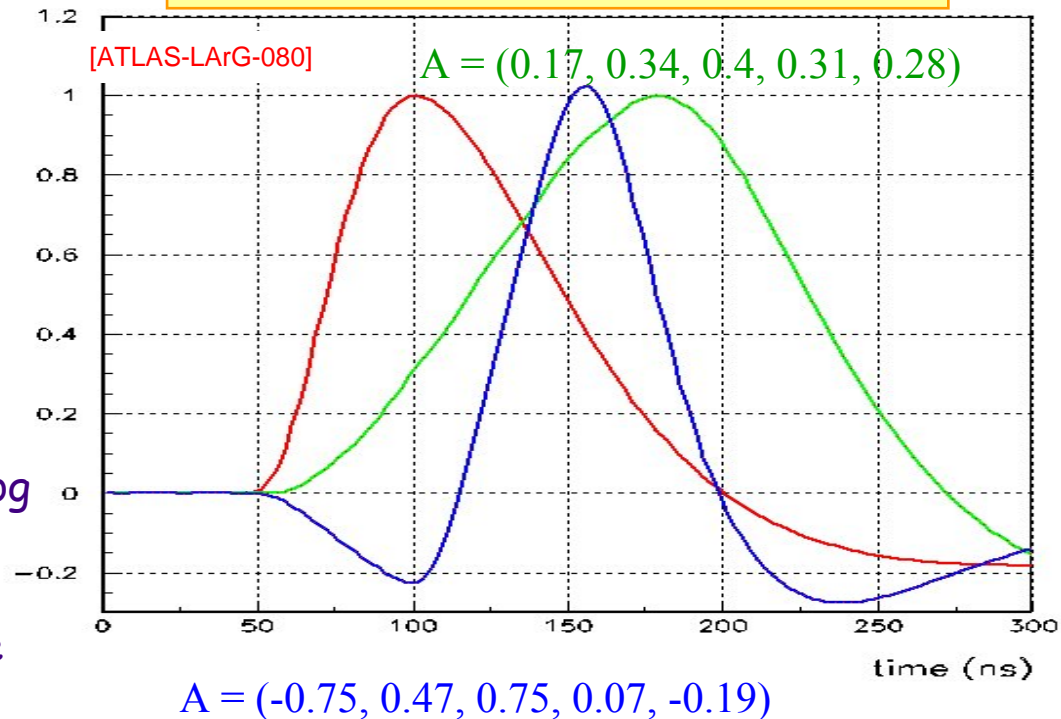


Exemple : ATLAS "multiple sampling"

©L. Serin (LAL)

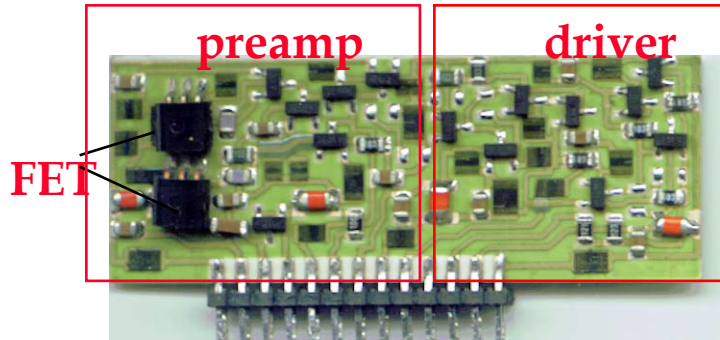
- **Slowing down the signal**
 - Reduction of series noise
 - Similar to a simple integration
- **Accelererating the signal**
 - Reduction of pileup noise
 - Similar to a differentiation
- **Measuring the timing**
- **Some questions**
 - How does-it compare to an analog filter
 - How many samples are needed ?
 - What accuracy is needed on the waveform and on the autocorrelation ?
 - What analog shaping time is needed ?
 - Is the analog filter really useful ?

Signal before and after digital filtering



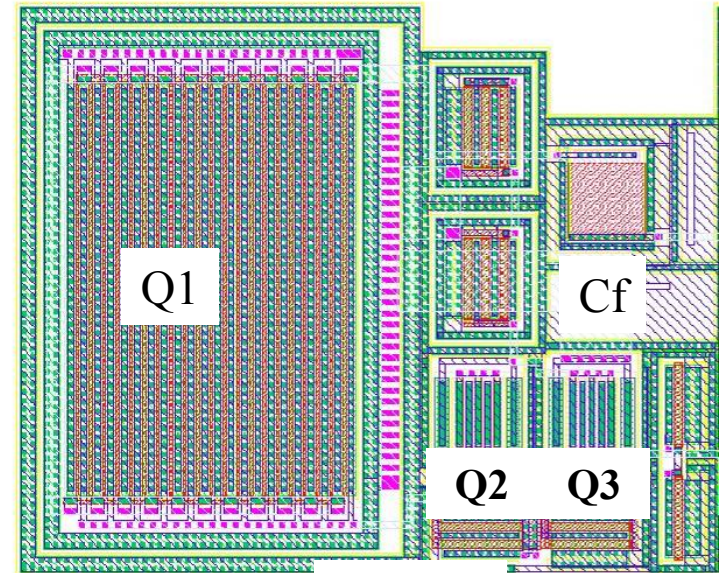
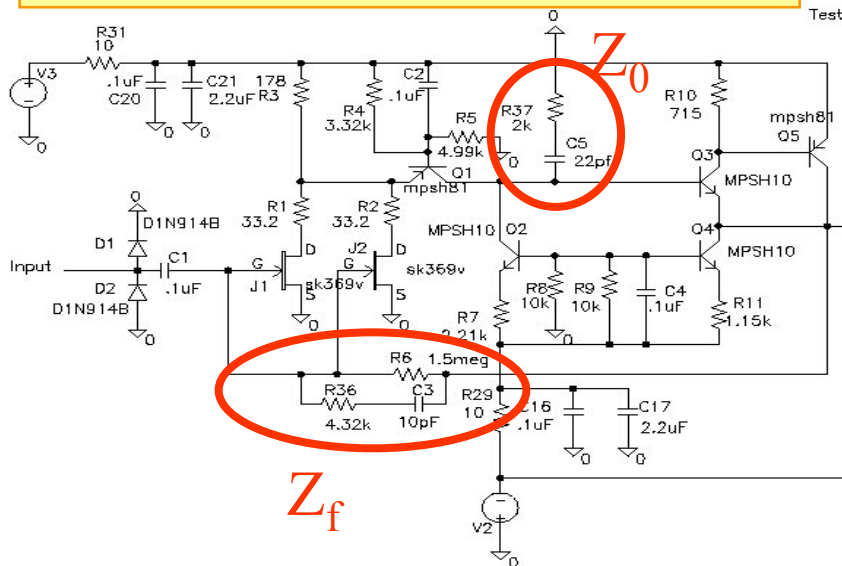
(R)evolution of analog electronics (1)

Acces to microelectronics



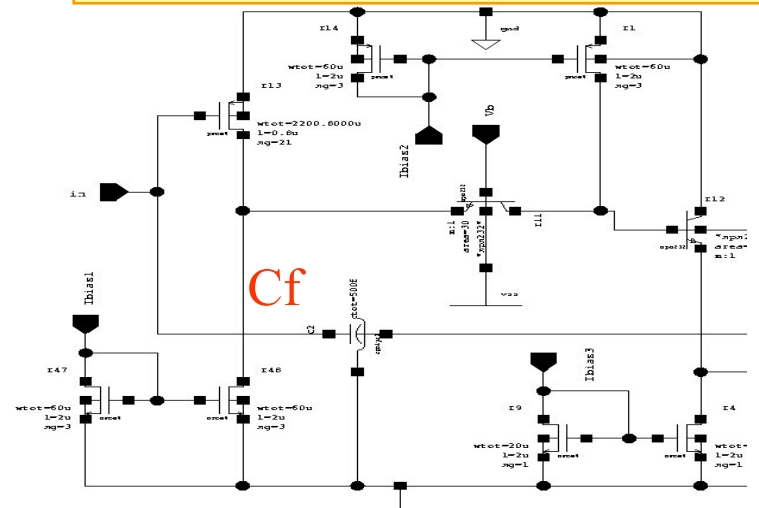
6 cm

Charge preamp in SMC hybrid techno



100 μm

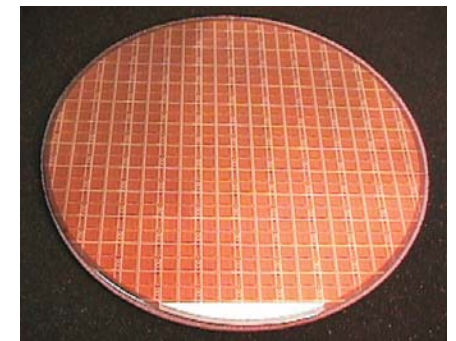
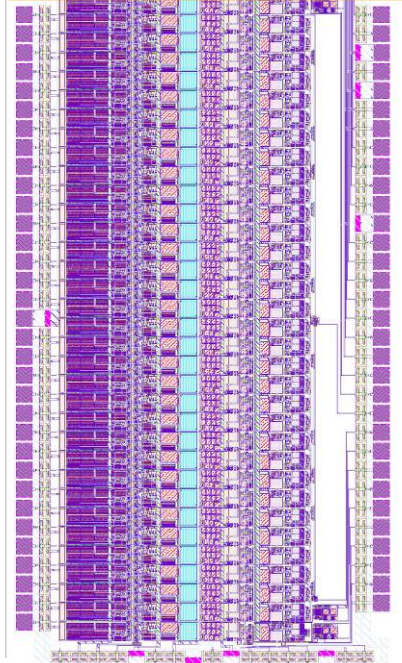
Charge preamp in 0.8 μm BiCMOS



(R)evolution of analog electronics (2)

- **ASICs : Application Specific Integrated Circuits**
 - Access to foundries through **multiproject runs (MPW)**
 - Reduced development costs : 600-1000 €/mm² compared to dedicated runs (50-200 k€)
 - **Full custom layout, at transistor level**
 - mostly **CMOS & BiCMOS**
- **Very widespread in high Energy Physics**
 - High level of integration, limited essentially by power dissipation and parasitic couplings (EMC)
 - Better **performance** : reduction of parasitics
 - Better **reliability** (less connections)
 - But **longer developpement time**

Layout 32ch ASIC

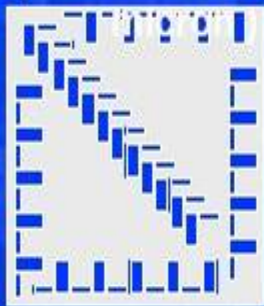


300 mm wafer (IBM)

Processing of ASICs

From Sand to ICs...

RETICLE
(Pattern with 0.7 micron
apertures ie 4 X 0.18



Lithography.



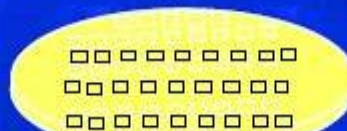
Silicon Wafer



**Light
Sensitive
Coating.**



**Multiple Layers.
>350 process steps.**

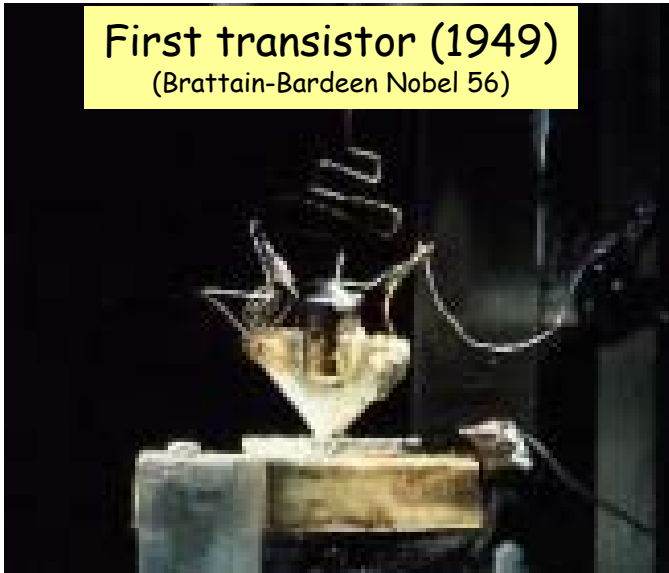


**CREATING > 125 million
TRANSISTORS ON EACH
MICROPROCESSOR;**

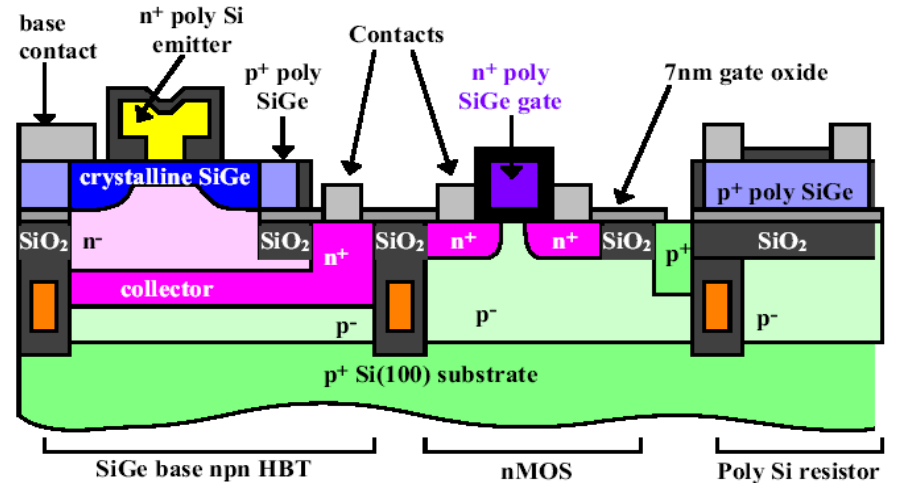
**WITH FEATURES 1/2000th THE
WIDTH OF A HUMAN HAIR.**

Evolution of technologies

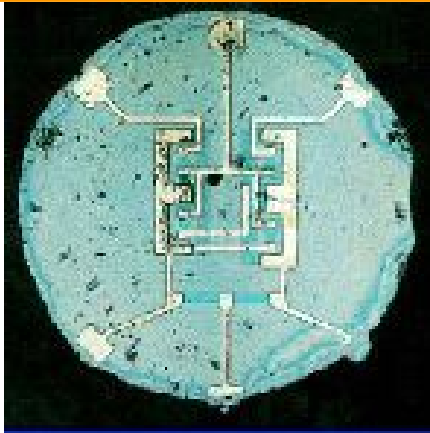
First transistor (1949)
(Brattain-Bardeen Nobel 56)



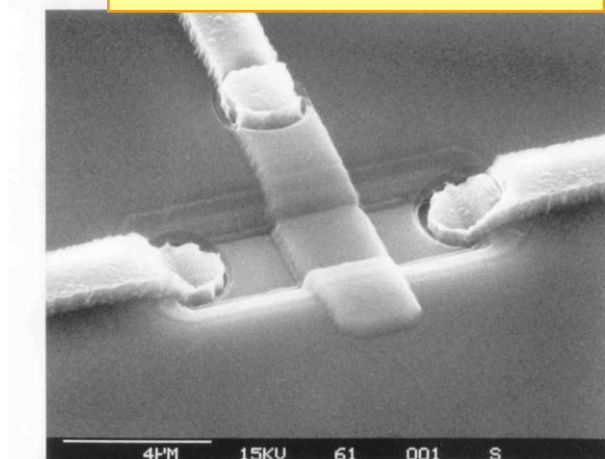
SiGe Bipolar in 0.35μm monolithic process



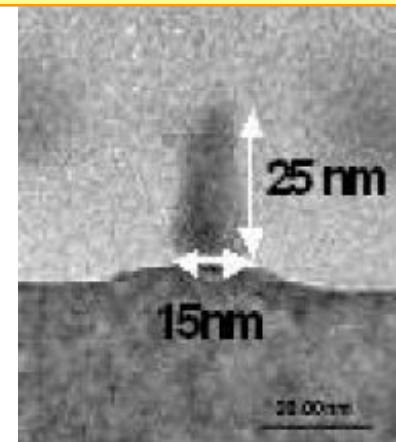
First planar IC (1961)



5 μm MOSFET (1985)



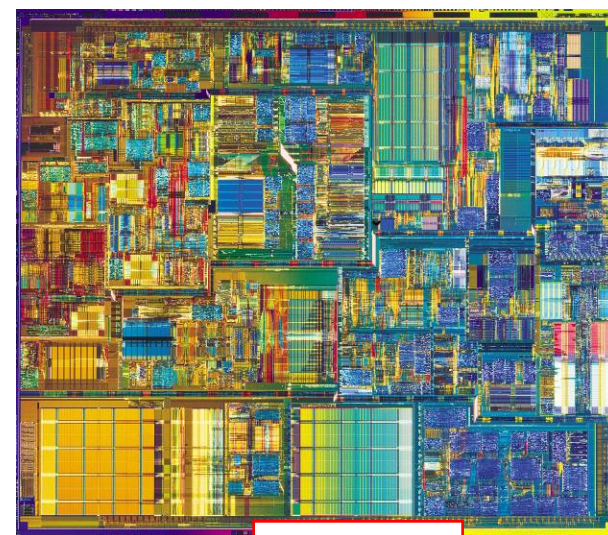
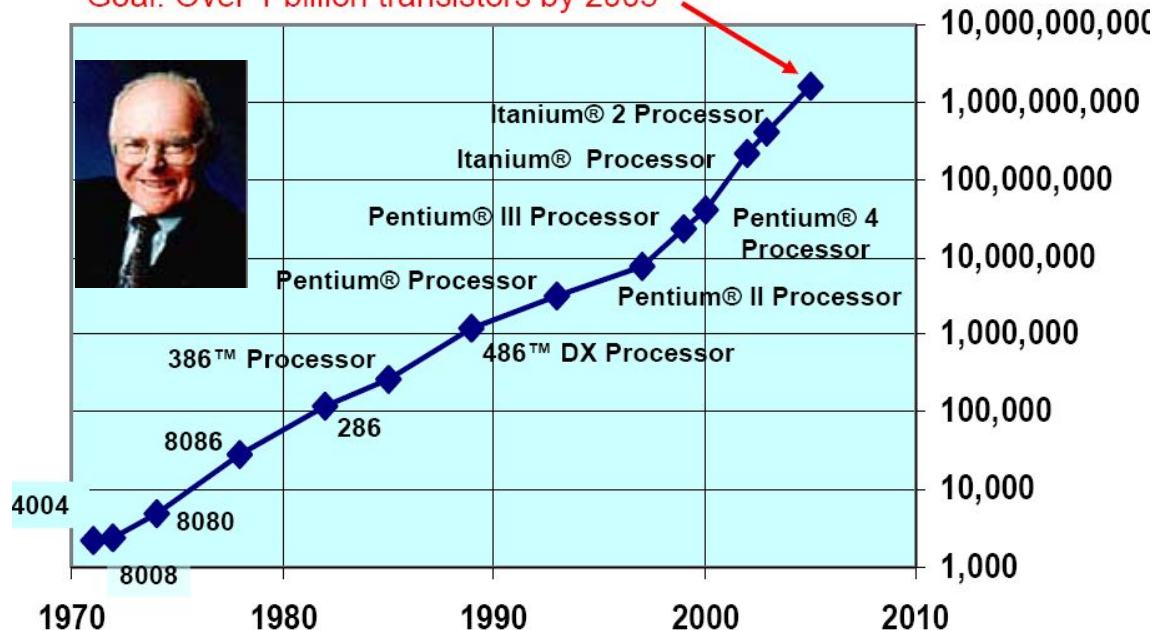
15 nm MOSFET (2005)



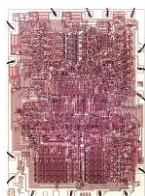
Evolution of CMOS technologies

Moore's law : doubling every 2 years

Goal: Over 1 billion transistors by 2005



Pentium 4

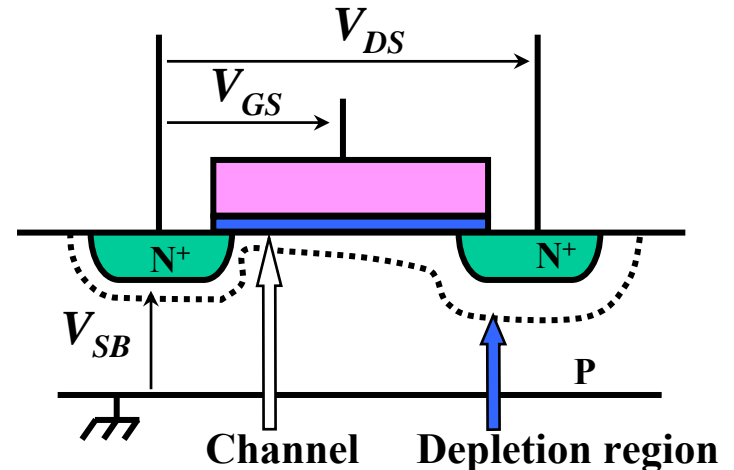
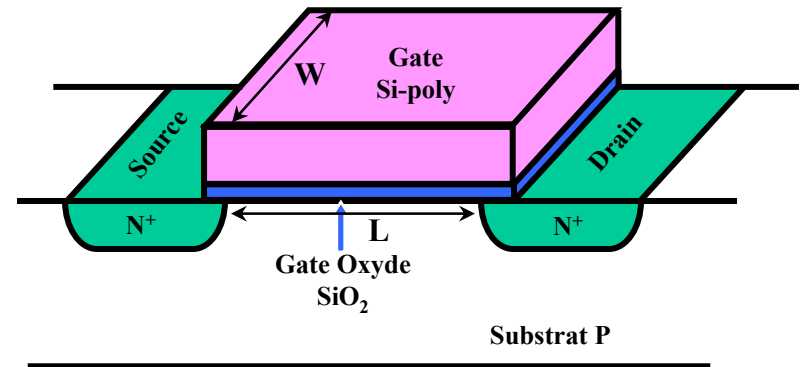


4004

Microprocesseur	4004	8086	i386	Pentium	Pentium 4
Année	1971	1978	1985	1993	2000
Nb. Bits	4	16	32	64	64
Horloge (Hz)	108k	10M	33M	66M	1.5G
Mémoire adressable (bytes)	640	1M	16M	4G	64G
Technologie (µm)	10	3	1	0.8	0.18
Nb transistors	2300	29000	275000	3.1M	42M
Tension alim (V)	12	5	5	5/3.3	1.3 interne

« CMOS scaling »

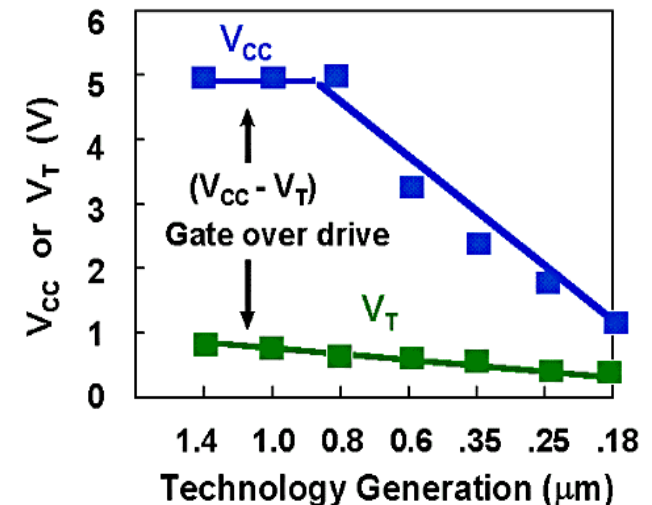
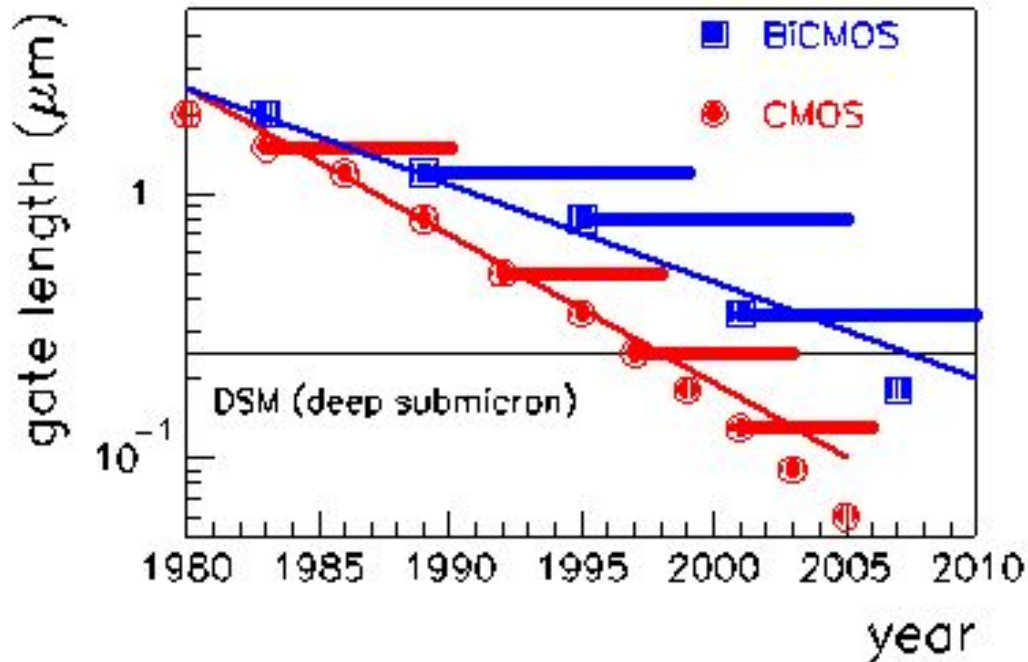
- **Reduction of dimensions**
 - Gate length : L
 - Oxide thickness : t_{ox}
- **Reduction of power supplies**
 - Reduction of power dissipation
- **Improvement of speed in $1/L^2$**
 - Transconductance : g_m a W/L
 - Capacitance : C a WL
 - speed : $F_T = g_m/C$ a $1/L^2$
- **Reduction of costs (?)**
 - Increase of integration density
- **Radiation hardness in bonus !**
 - Less trapping in gate oxide



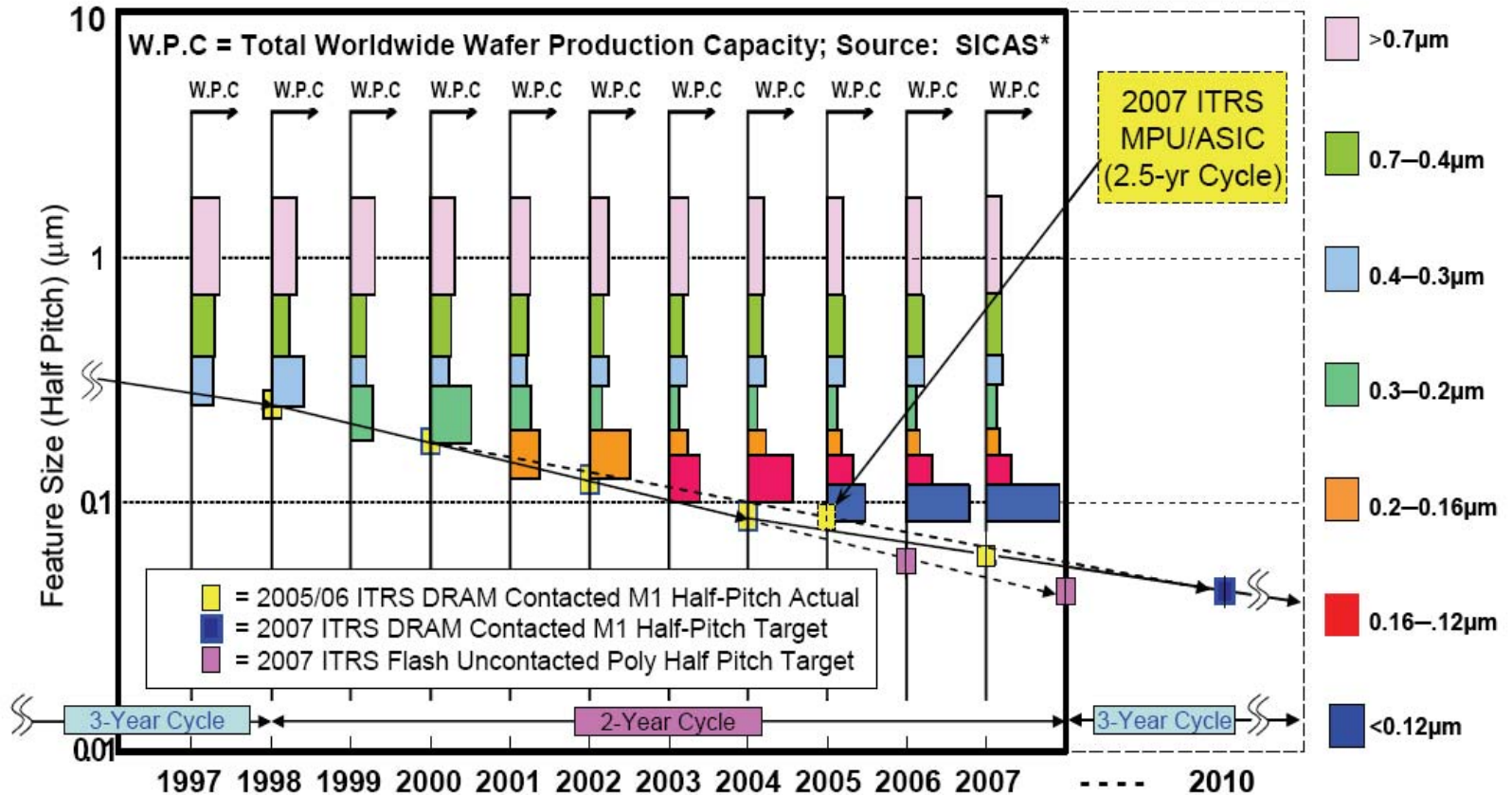
Principle of Nchannel MOSFET

Evolution of CMOS technologies (2)

- Differences between analog/mixed signal and digital technologies
 - Very fast evolution of digital technologies (faster design migration)
 - More « perene » analog technologies (SiGe, BiCMOS...) (driven by mobile telecom and automotive)
 - A visible split occurring
- More difficult analog design in low voltage
 - « no more headroom for signals »



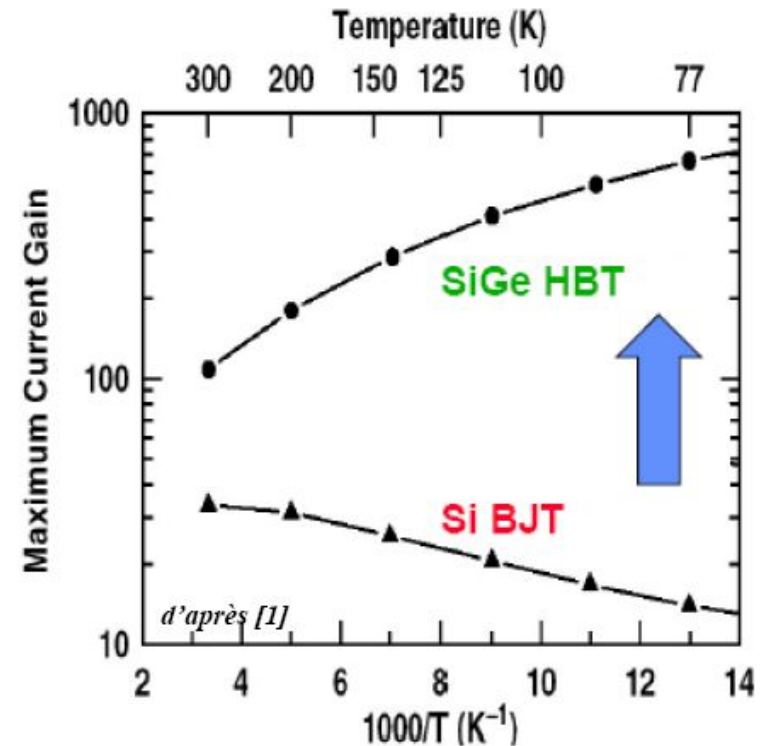
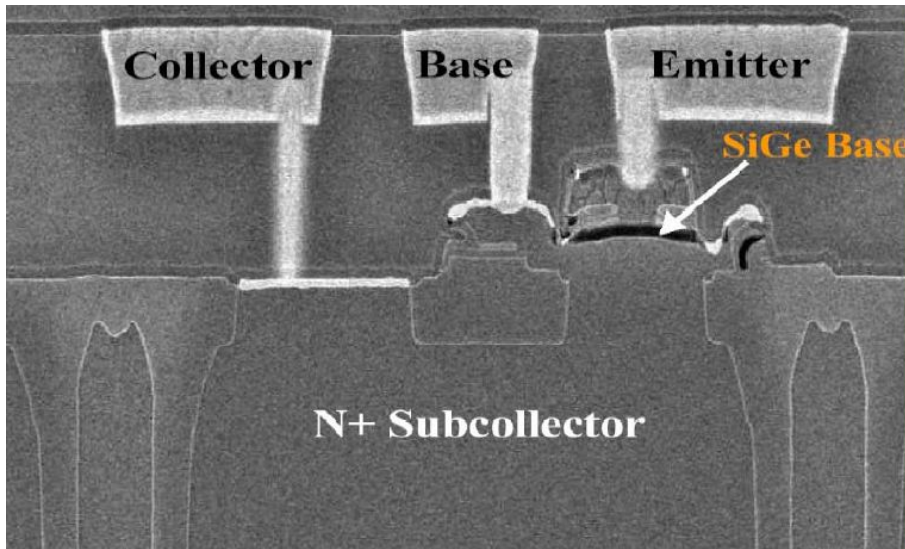
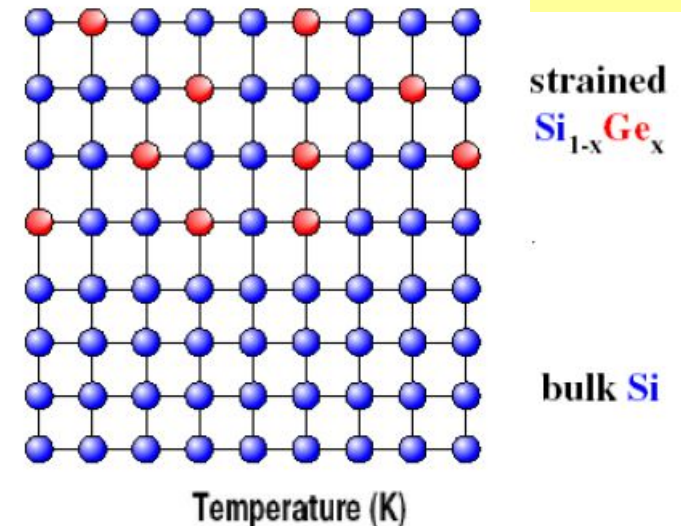
Semiconductor Industry Roadmap



SiGe technology

© R. Hermel

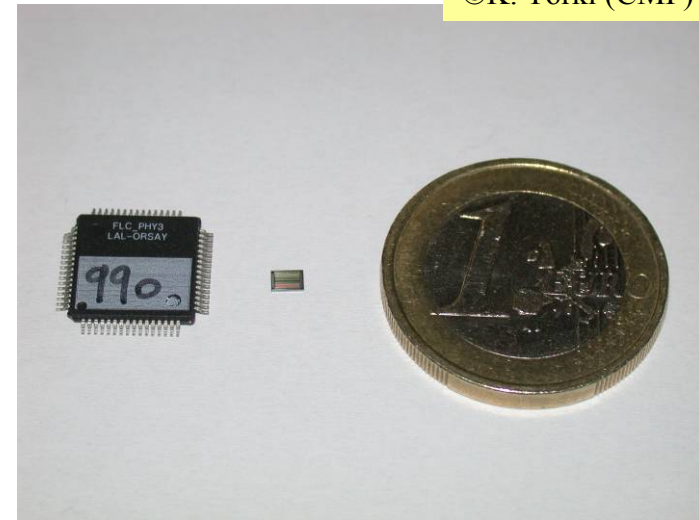
- Faster bipolar transistors for RF telecom
 - Better mobility and FT
 - Better current gain (beta)
 - Better Early voltage
 - Interesting improvement at low T
 - Compact CMOS (0.25 or 0.35 μm) for mixed-signal design



Cost of ASICs

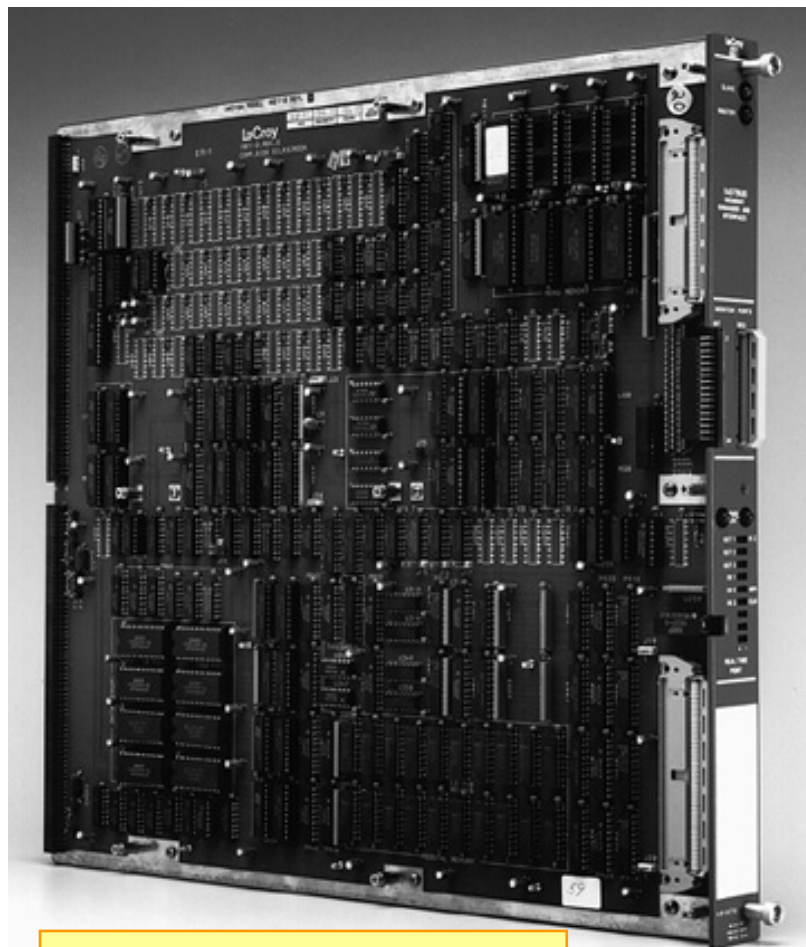
©K. Torki (CMP)

- **MPW (multi-project wafers)**
 - CMOS 0.35 μ m (AMS) : 650 €/mm²
 - BiCMOS SiGe 0.35 μ m (AMS) : 900 €/mm²
 - CMOS 0.13 μ (STm) : 2500 €/mm²
 - CMOS 90 nm (STm) : 5000 €/mm²
 - Usually a few 10 to 100 pieces in a MPW run
- **Production runs**
 - Masks : 91 k€ (CMOS 0.35 μ m)
 - 8" wafers : 4 k€, useful area : 25 000 mm² = several thousands of chips
- **Packaging**
 - Ceramic : 20-30€/chip
 - Plastic : 2k€ + 1-2 €/chip
- **Example : chip 10mm² 16 channels**
 - 100 chips (MPW) : 120€/chip, 7€/channel
 - 10 000 chips (4wafers) : 12€/chip < 1€/channel

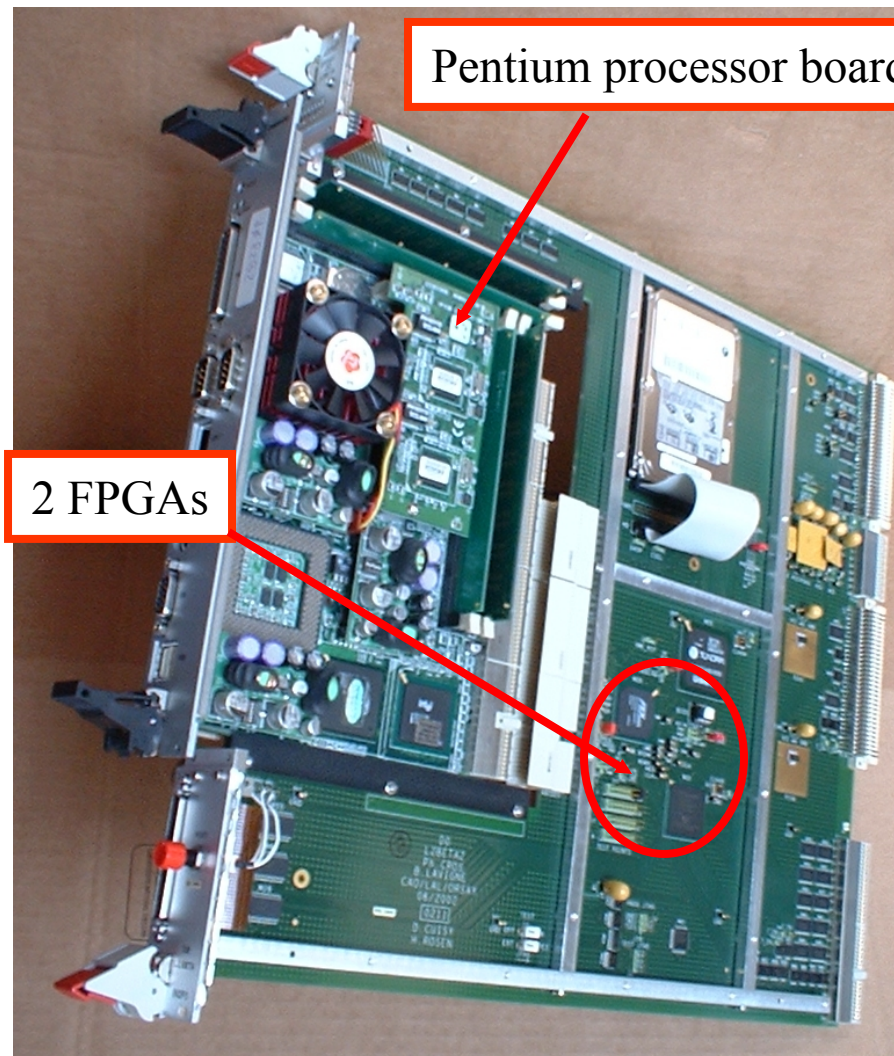


(R)evolution of digital electronics (1)

- From stacks of circuits to FPGAs : programmable gate arrays



Fastbus controller (1990)



Pentium processor board

2 FPGAs

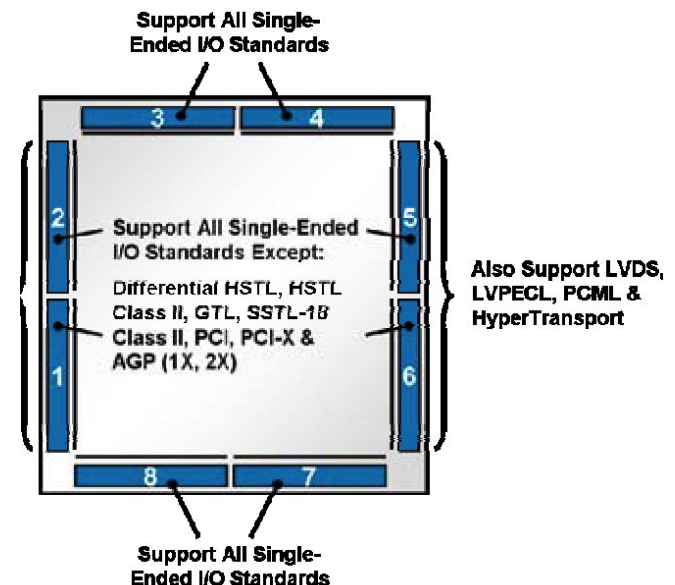
(R)evolution of digital electronics (3)

■ Reduction of digital logic levels

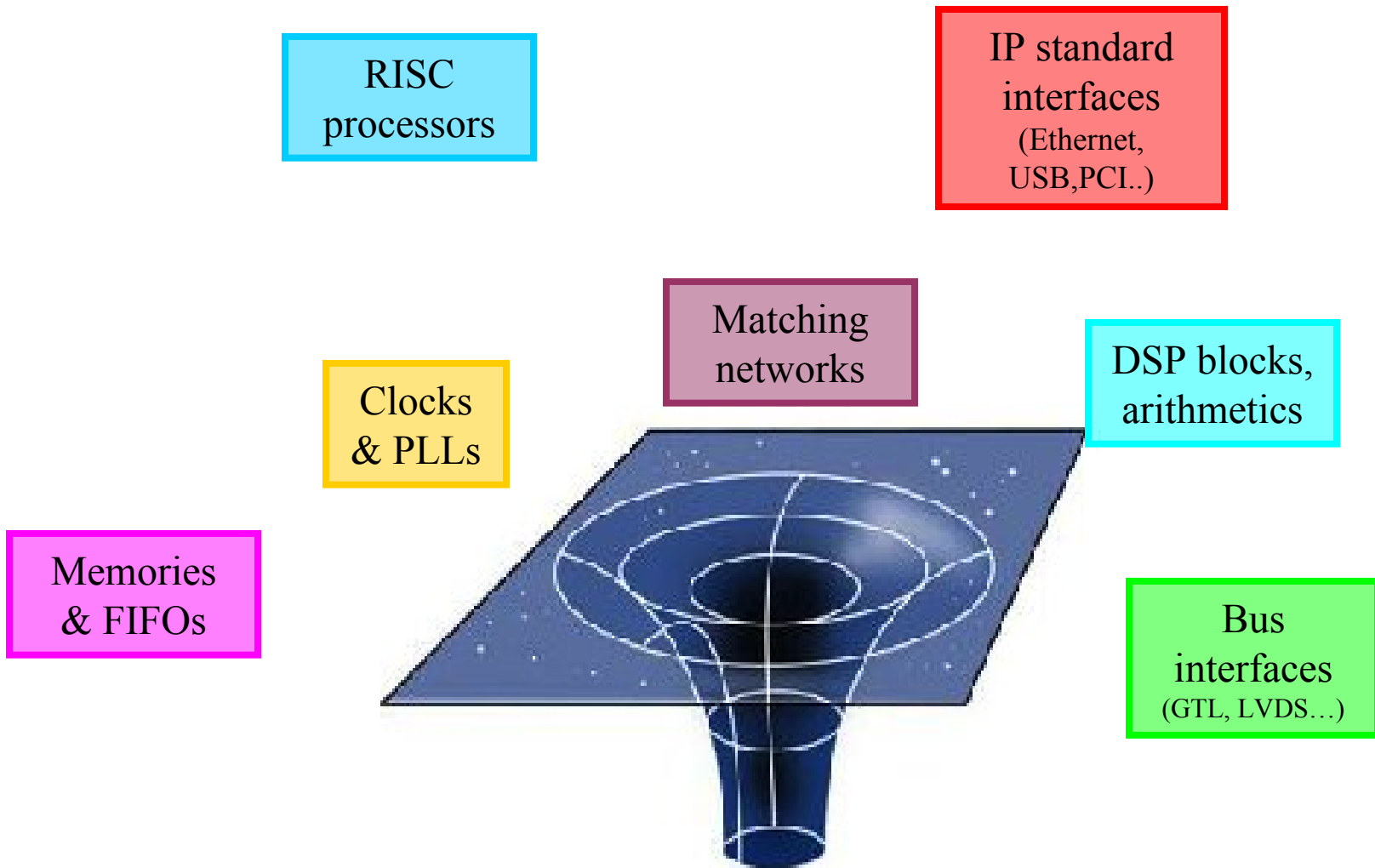
- 1980 : **TTL** : 0-5 V
- 2000 : **LVDS** : Low Voltage (± 400 mV) Differential Swing
- Better signal integrity (EMC)
- Reduction of power supplies 5V \rightarrow 3.3V \rightarrow 2.5V \rightarrow 1.2V

■ Components : the **revolution** of **FPGAs** :

- = Field **Programmable** Arrays (**Altera**©, **Xilinx**©)
- 4-40 millions gates (55M in a Pentium4)
- RISC 32bits processors
- 10 Mbits resident memory
- 2000 pins 1300 I/O (inputs/outputs)
- 300 MHz operation



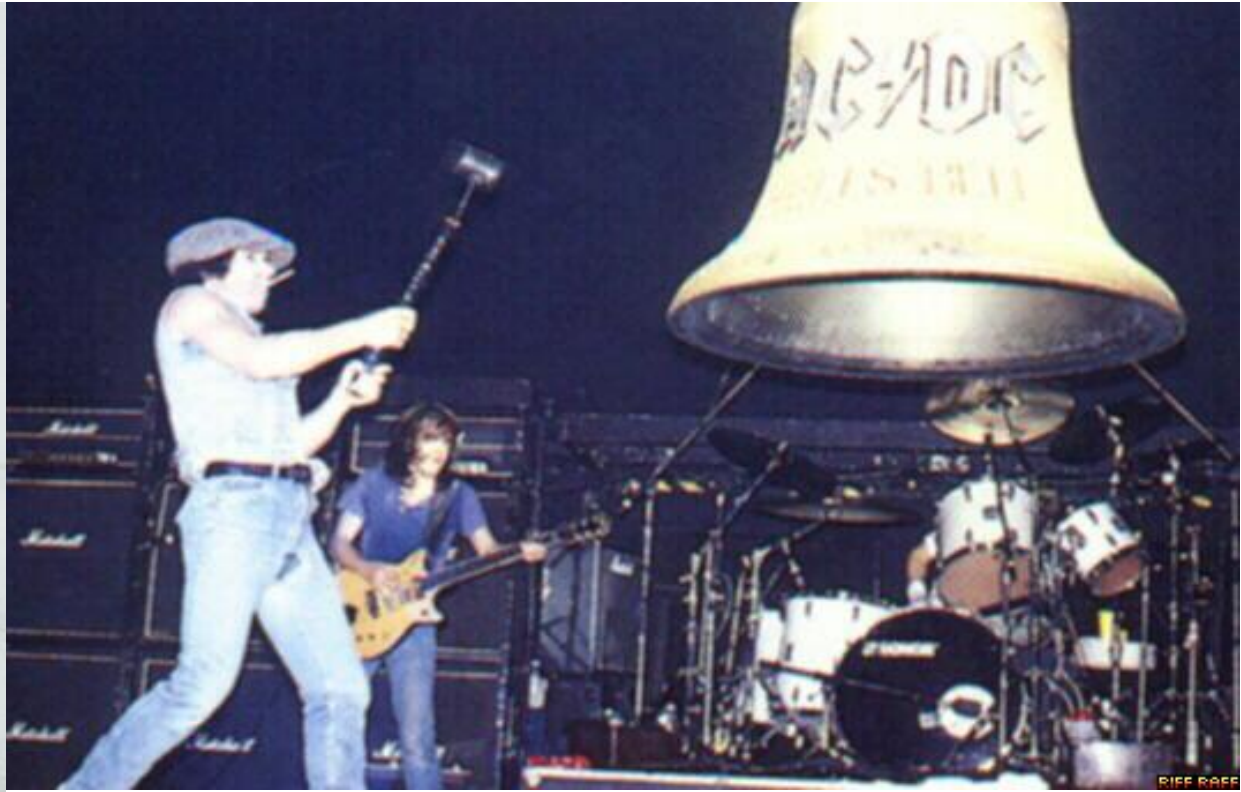
FPGAs as blackhole of digital electronics ?



Electromagnetic compatibility (EMC-EMI)

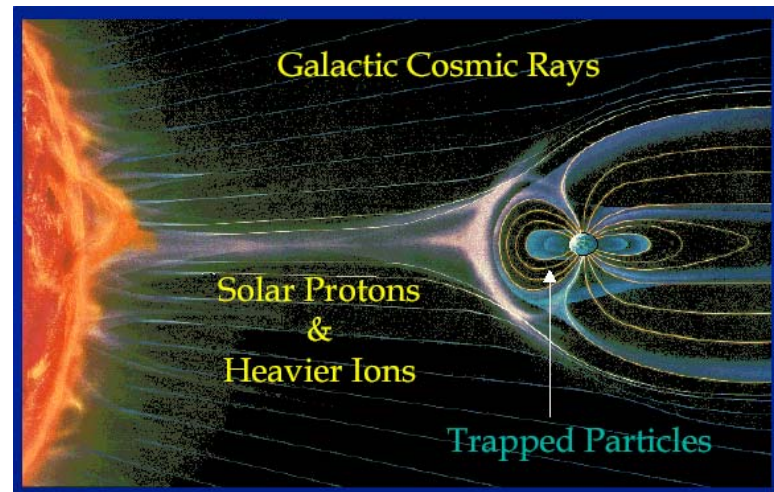
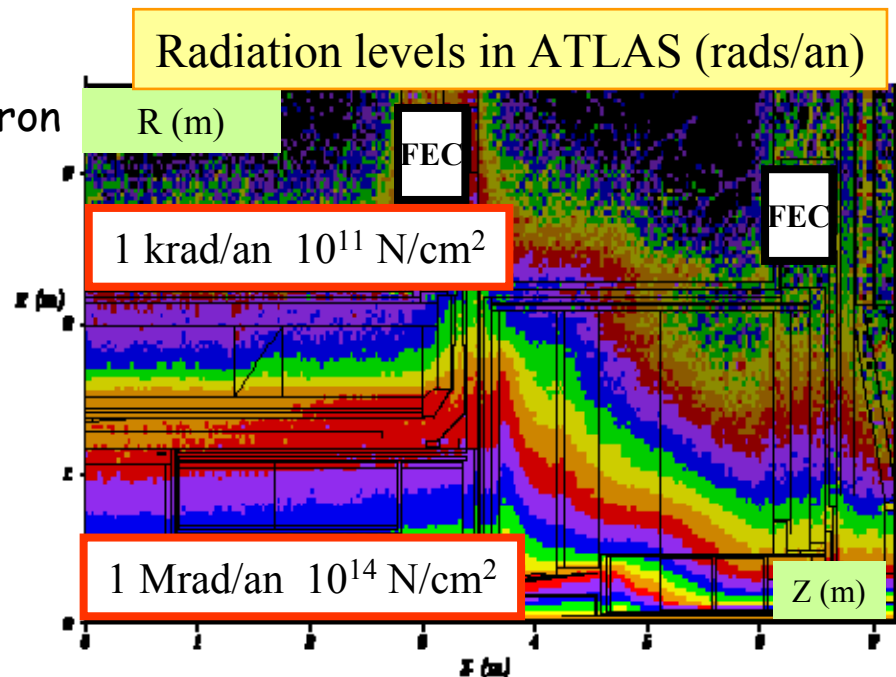
■ Coexistence analog-digital

- Capacitive, inductive and common-impedance couplings
- A full lecture !
- A good summary : there is no such thing as « ground », pay attention to current return



Effect of radiations on components

- **TID** : total ionising dose effects
 - Charge trapping in gate oxide
 - Alleviated in thin oxides (Deep SubMicron DSM)
 - Radiation tolerant layout techniques designed by CERN RD49 in $0.25\mu\text{m}$
- **NIEL** : non ionising energy loss
 - Cristal damage with neutrons
 - Beta drop in bipolar transistors
- **SEU** : Single Event Effect
 - Effect of large ionising impact : local charge deposition on critical nodes
 - SEU : single event Upset = bit flip
 - SEL : single Event Latchup : thyristor setting -> destructive !



Radiation hardness : space vs LHC

	<u>Space missions</u>	<u>LHC experiments</u>
■ Mission Time	<i>10-15 years</i>	<i>10 years</i>
■ Service	<i>Not Possible</i>	<i>Impractical</i>
■ Electronics Reliability	<i>High</i>	<i>High</i>
■ Total Dose Requirements	<i>10 -100 krad</i>	<i>1 krad - 10 Mrad</i>
■ Non Ionizing Energy Loss (N)	<i>~0</i>	<i>10^{13}-10^{15} N/cm²</i>
■ Single Event Upsets	<i>IC's SEU characterised</i> <i>No Critical SEU Accepted</i>	
■ => Similar requirements		

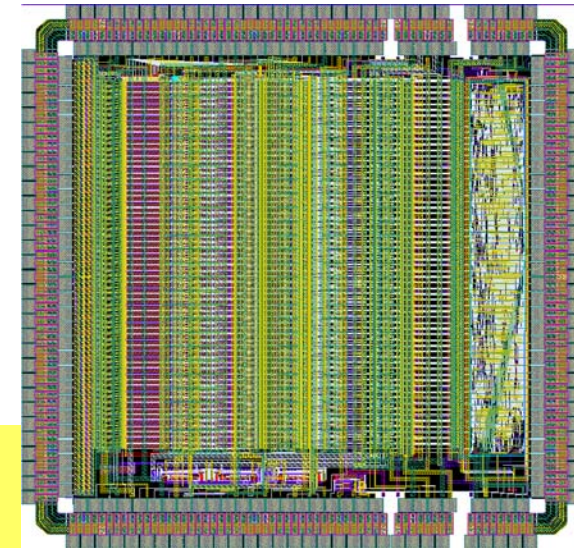
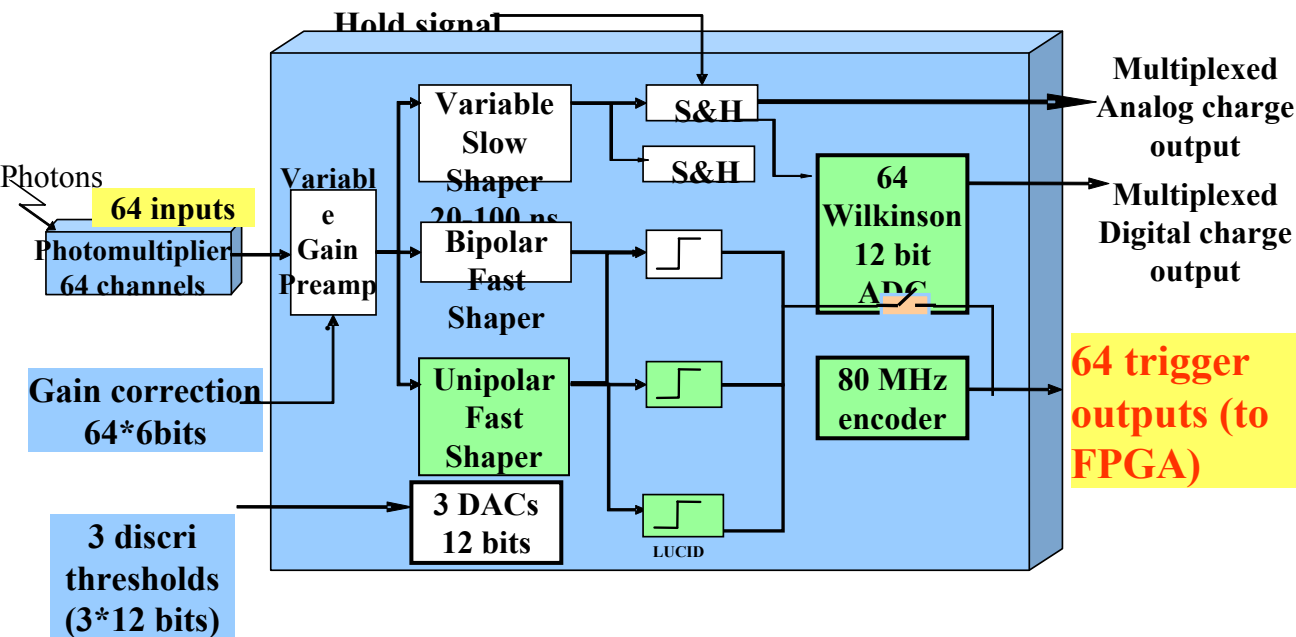


Examples and trends

- **More pixels => more integration**
- **System on chip => more integration !**
- **3D integration : still more integration !**

MAROC : 64 ch MAPMT chip for ATLAS lumi

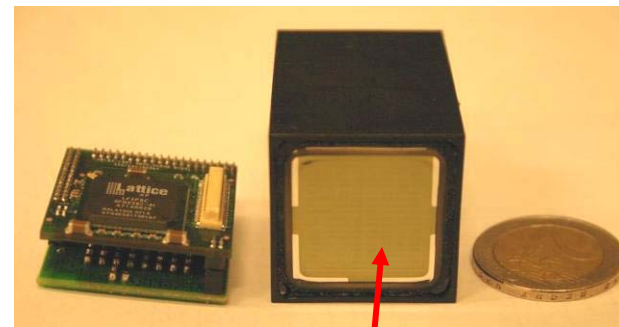
- Complete front-end chip for 64 channels multi-anode photomultipliers
 - Auto-trigger on 1/3 p.e. at 10 MHz, 12 bit charge output
 - SiGe 0.35 μm , 12 mm², Pd = 350mW



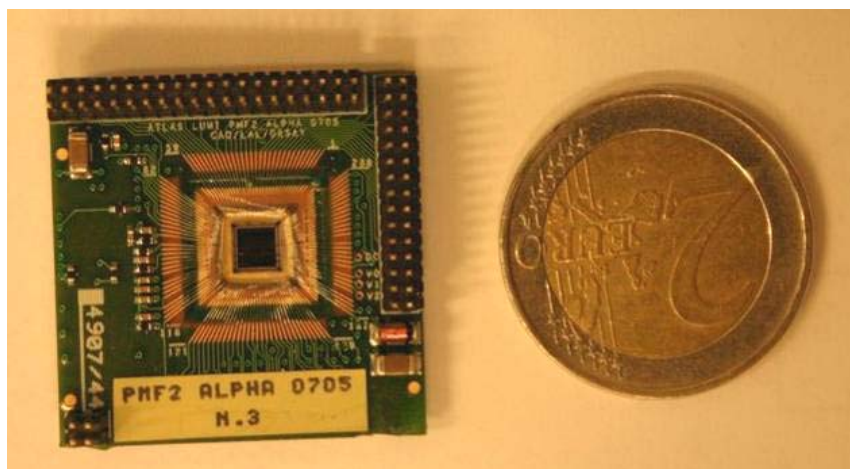
Active board pictures



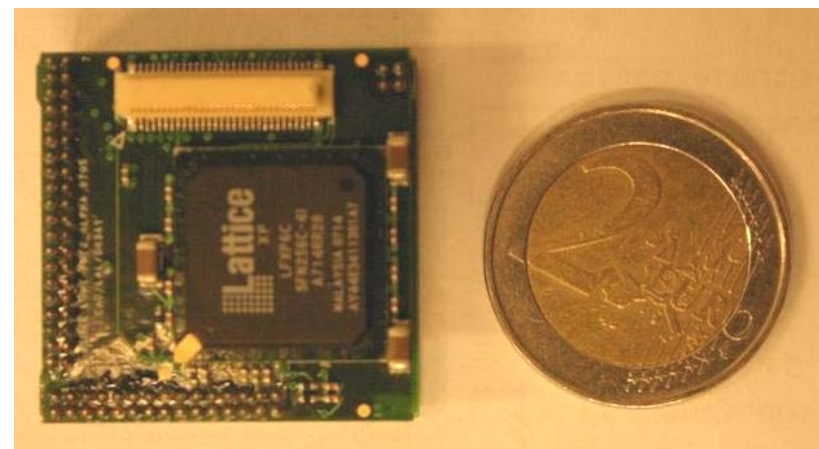
MAROC2 chip bounded at CERN



64 ch PMT

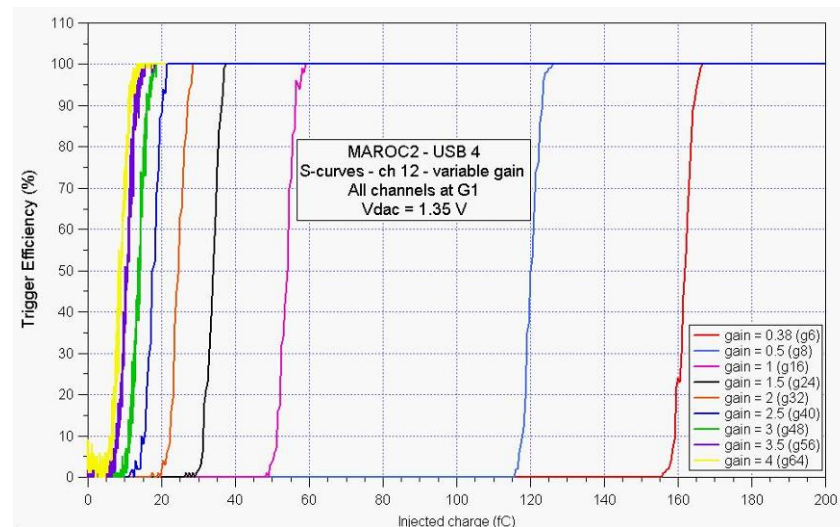
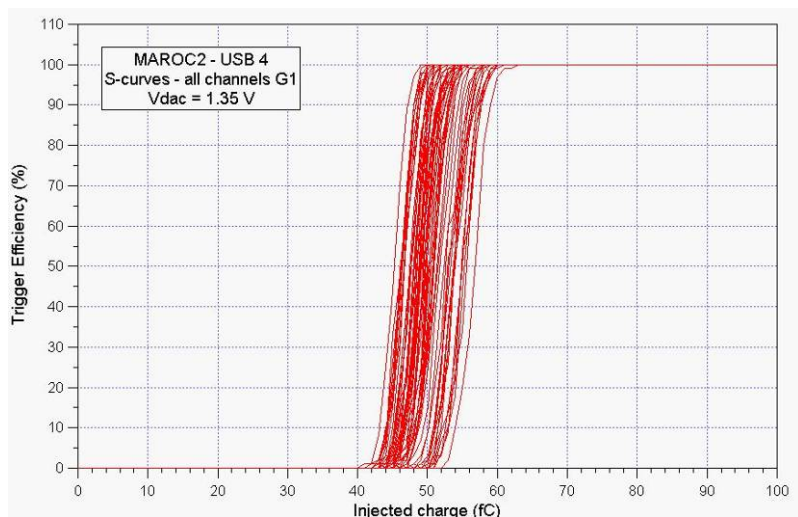


MAROC side

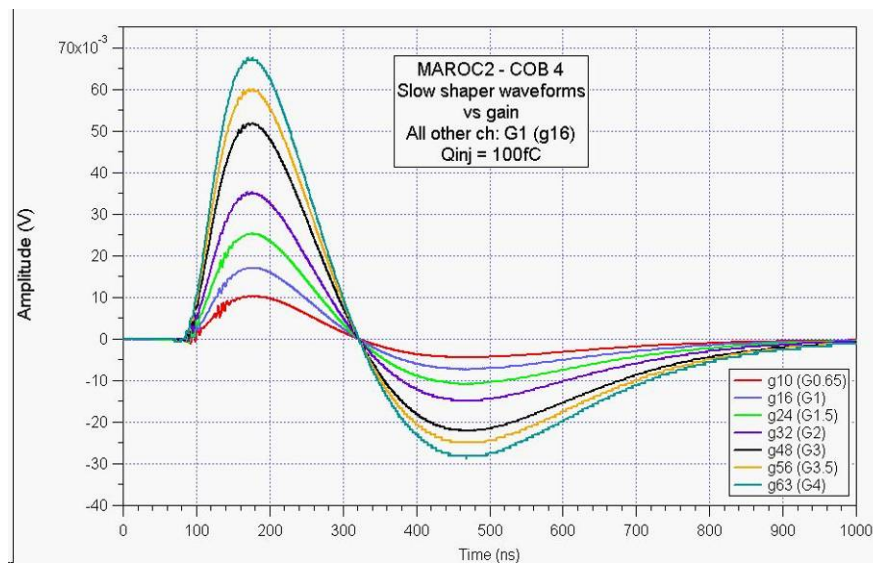
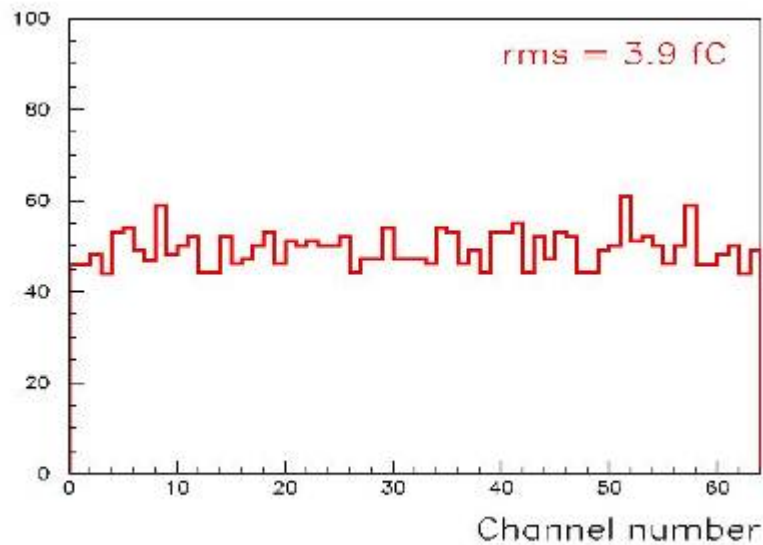


Lattice side

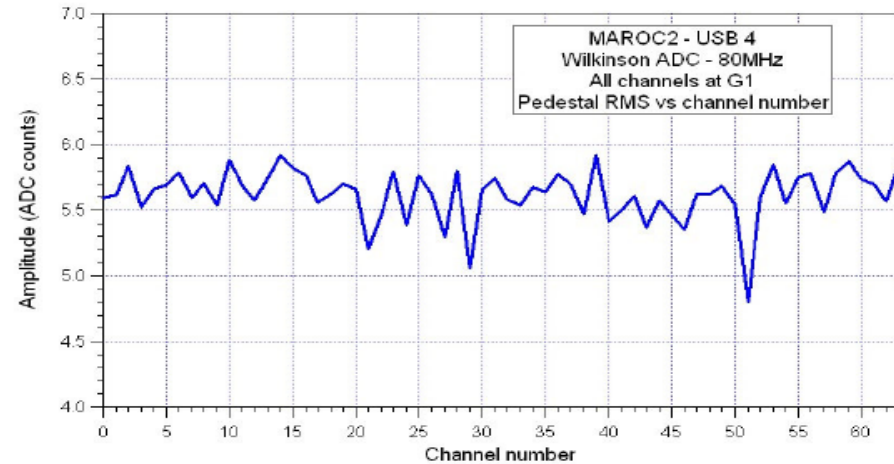
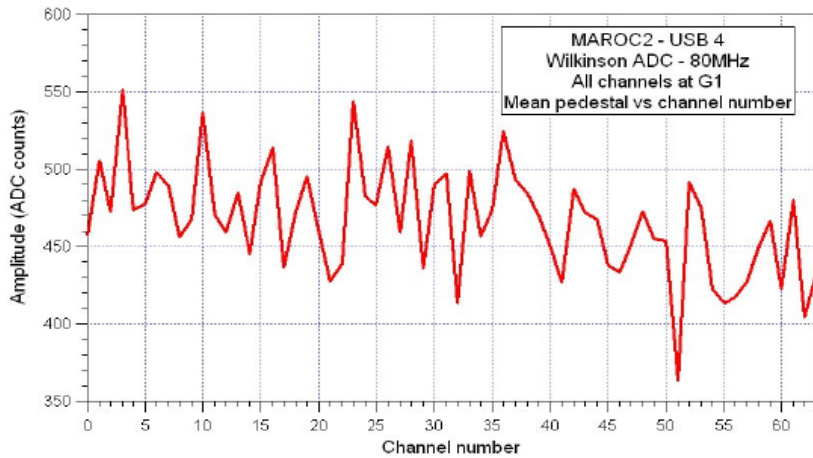
MAROC Efficiency curves



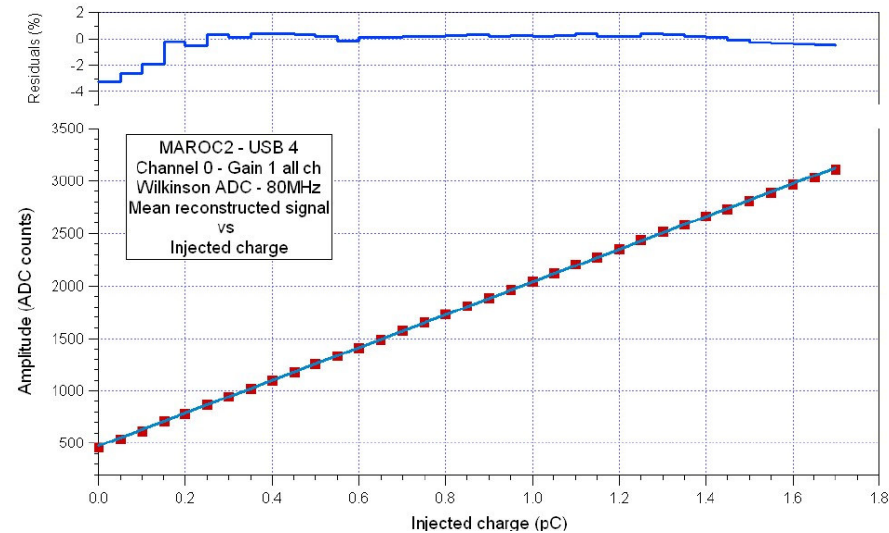
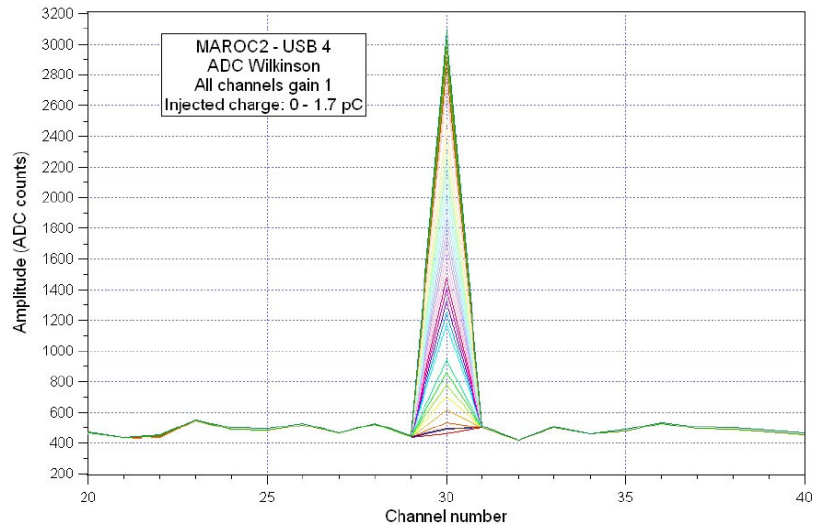
trigger Q 50



MAROC 2: Charge output Wilkinson ADC



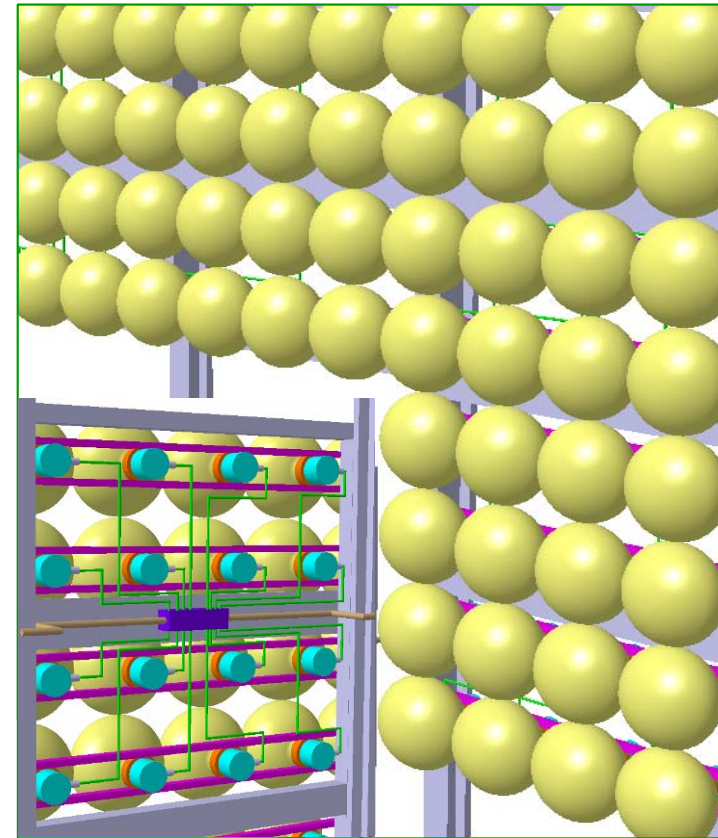
INTERNAL ADC



- Measurements performed with the internal Wilkinson ADC
- Linearity of $\pm 2\%$ approximately

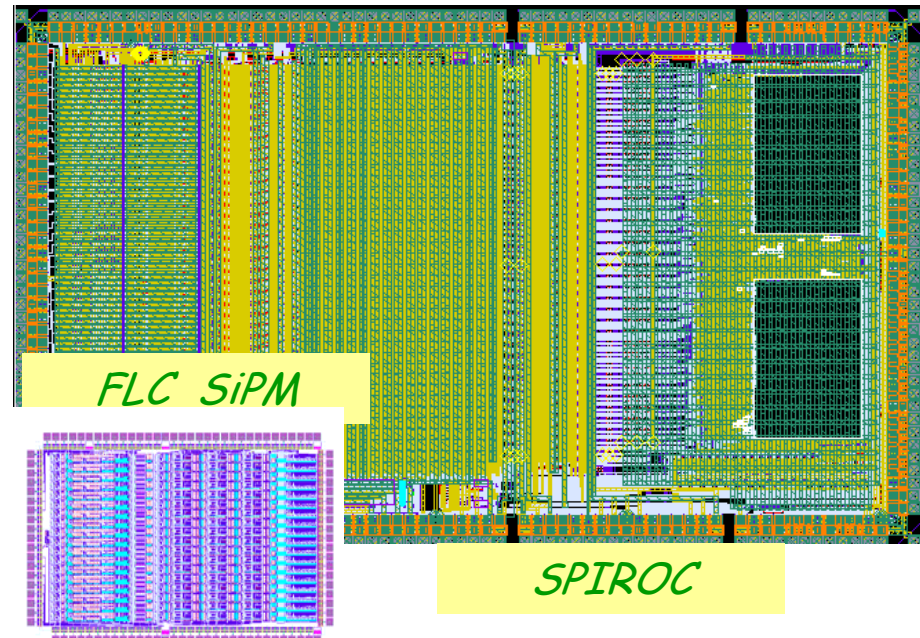
PMm² : large photodection area

- "PMm2" (2006 - 2009), funded by the ANR : LAL, IPNO, LAPP and Photonis
- Replace large PMTs (20") by groups of smaller ones (12")
 - central 16ch ASIC (MAROC like)
 - 12 bit charge + 12 bit time
 - water-tight, common High Voltage
 - Only one wire out (DATA + VCC)
 - Target low cost
 - Reuse many parts from MAROC & SPIROC
- Application : large water Cerenkov neutrino
 - 1ns time resolution
 - High granularity
 - scalability

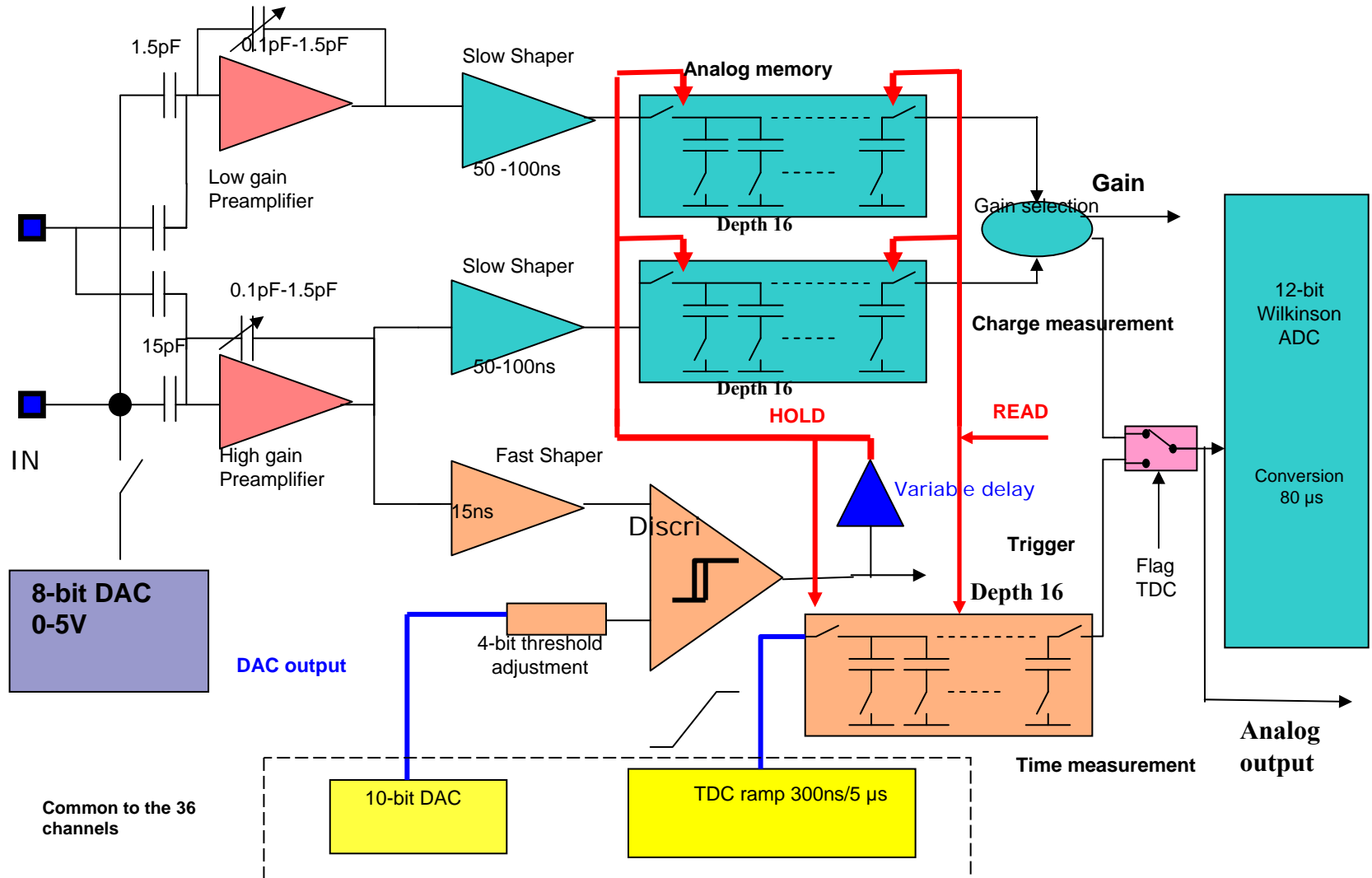


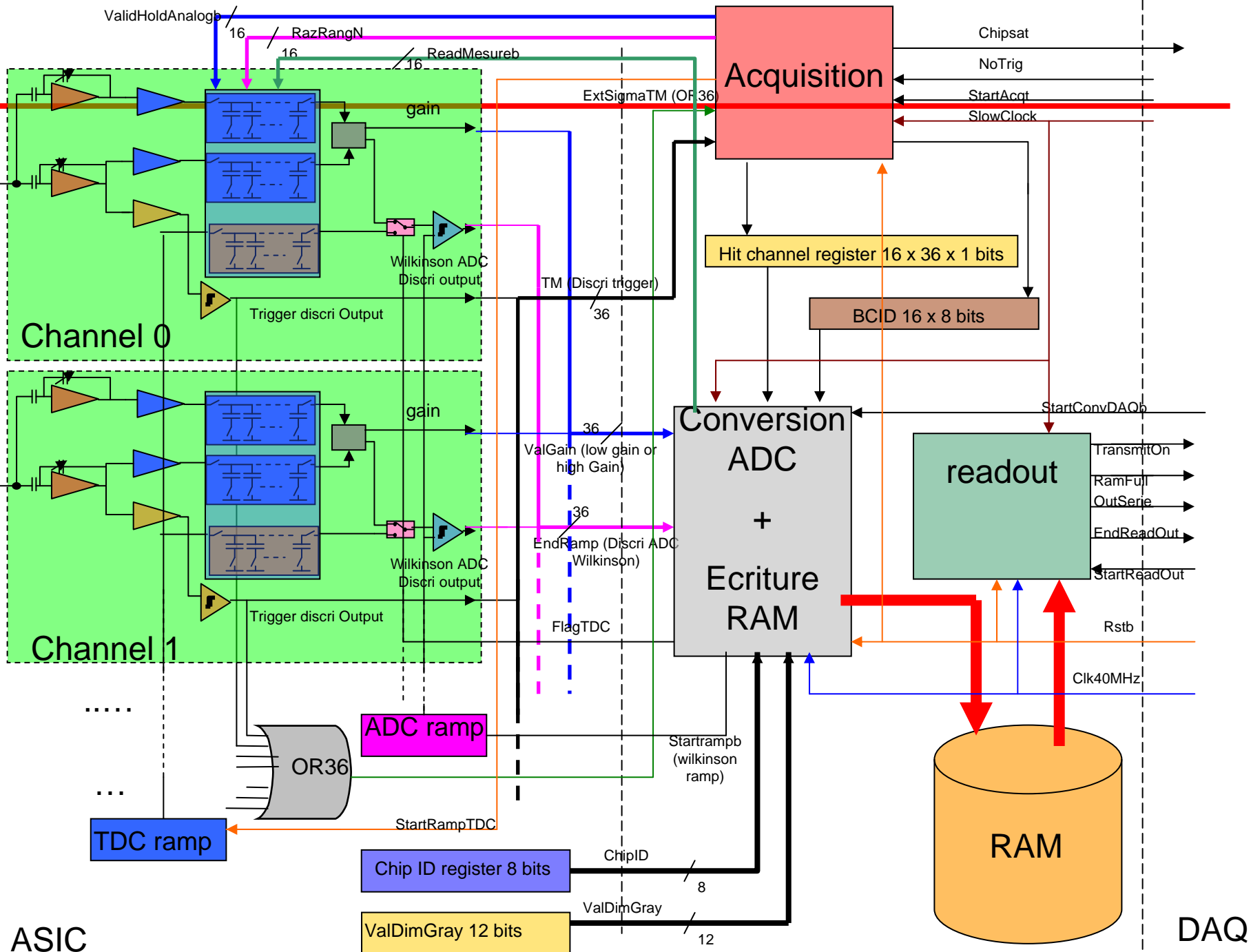
SPIROC : SiPM readout ASIC

- **Silicon Photomultiplier Integrated Read Out Chip**
 - Evolution from FLCSiPM
 - 36 channels
 - Charge measurement (15bits)
 - Time measurement ($< 1\text{ns}$)
 - many SKIROC, HARDROC, and MAROC features re-used
 - Submitted in june 07 in SiGe 0.35 μm AMS
- **Collaboration with DESY for ILC hadronic calorimeters**
 - 9000 channels used in test beam in 2004-2008
 - Production in 2009 for Eudet module



SPIROC : one channel



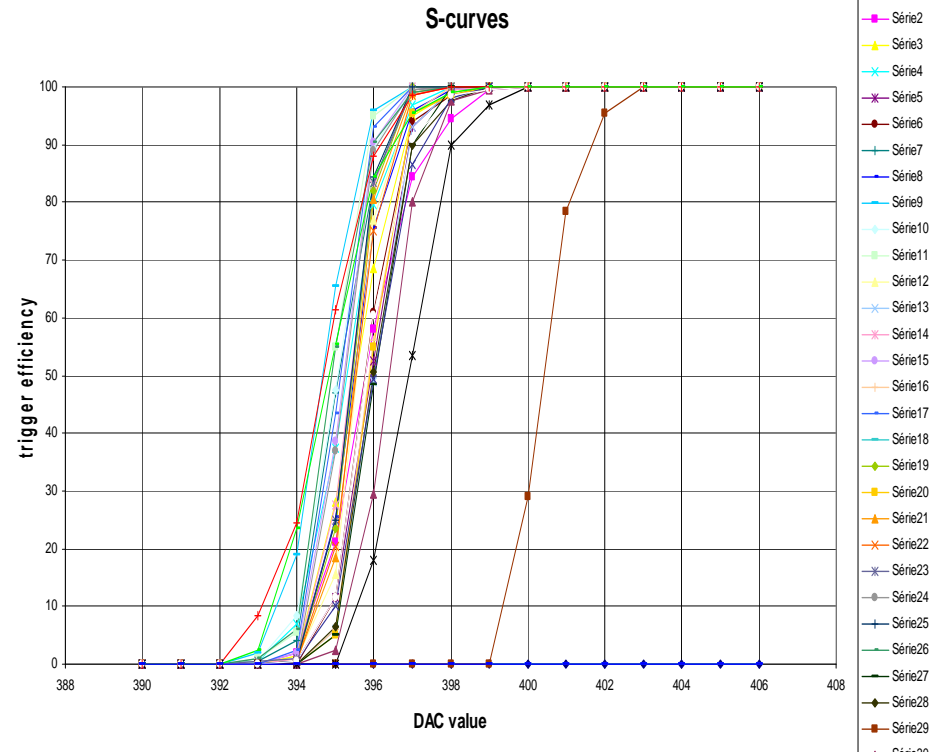
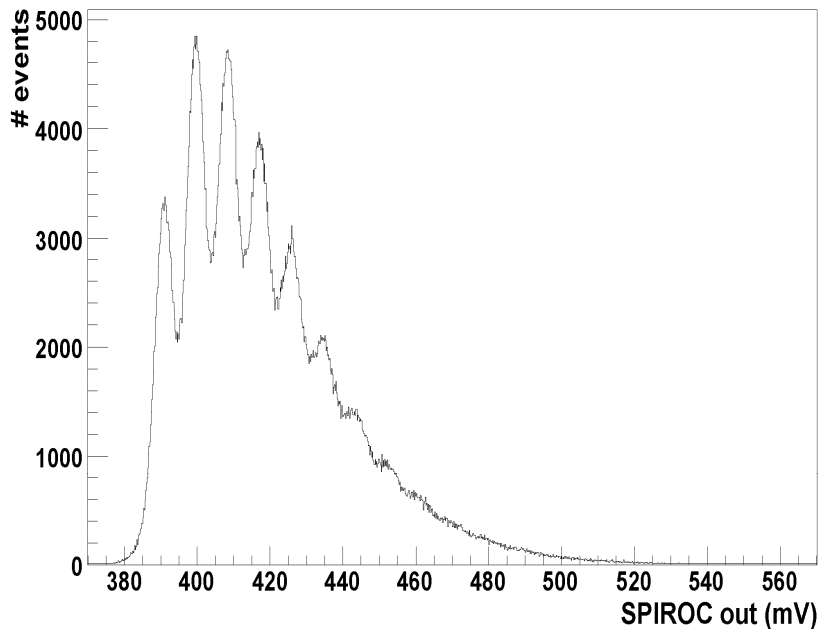


SPIROC performance

■ Good analog performance

- Single photo-electron/noise = 8
- Auto-trigger with good uniformity
- Complex chip : many more measurements needed

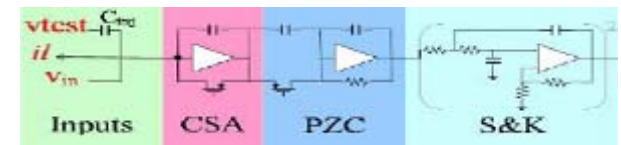
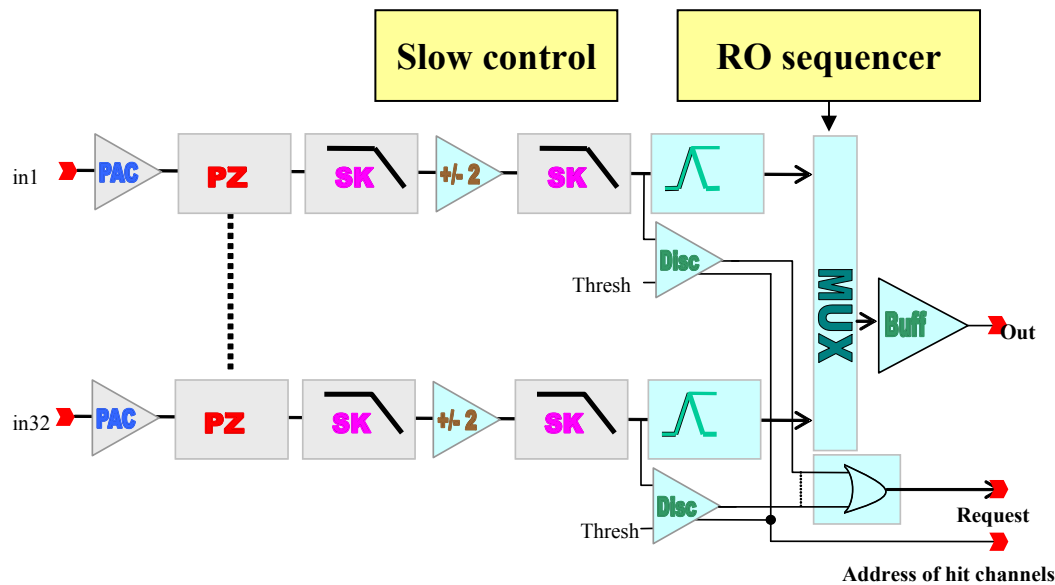
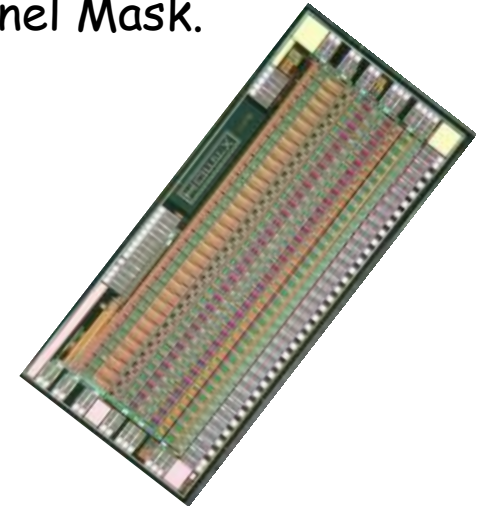
SiPM 753 SPIROC HG 100fF 50ns external hold



Idef-X 2.E for ECLAIRs.

- 32 channels. Muxed output
- 2.2 mW/ ch.
- Slow control => many parameters tunable
- Self triggered /1 Thresh/channel.
- $1\mu\text{s}$ - $10\mu\text{s}$ selectable shaping.
- deal with both signal polarities.
- Peak detector, $\sim 200\text{mV/fC}$.
- sparsification and « smart » readout.

- Detector Leakage comp.
- Test/Calib inputs
- Channel Mask.



Idef-X: performances

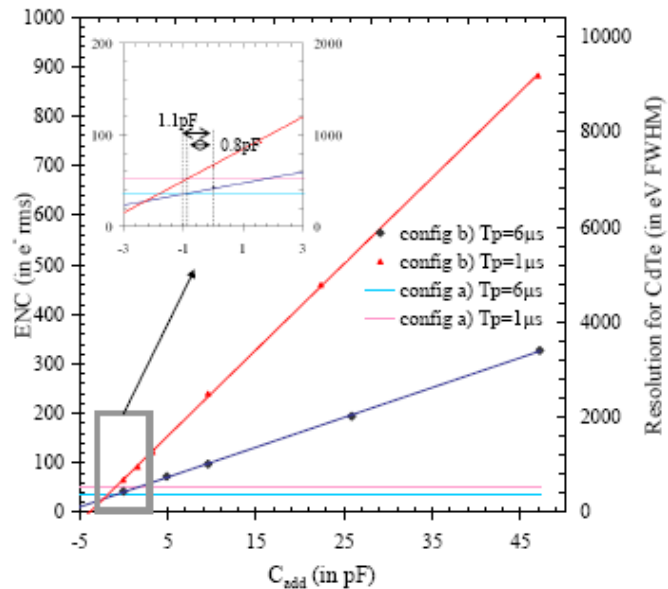


Fig. 4. Influence of the input additional capacitance. As expected, the lowest sensitivity of the chip to the input capacitance on its noise performance is obtained at the highest peaking time: at $6\mu\text{s}$, the slope is evaluated to $6\text{e}^-/\text{pF}$. The comparison of these plots with the ENC values obtained in config (a) is done to extract the parasitic capacitance of the detector board.

Low Thresh. $\ll 4\text{keV}$

**Production for flight model
out from fab in may 2008**

ISOR: CdTe Pt/Pt $4 \times 4 \times 0.5 \text{ mm}^3$ / 180V / 0°C

ECLAIR: IDef-X V1.0: CdTe In/Pt $4 \times 4 \times 0.5 \text{ mm}^3$ / 600V / 24°C

RAT IDef-X v1.0 : CdTe In/Pt $2.5 \times 2.5 \times 0.5 \text{ mm}^3$ / 340V / 24°C

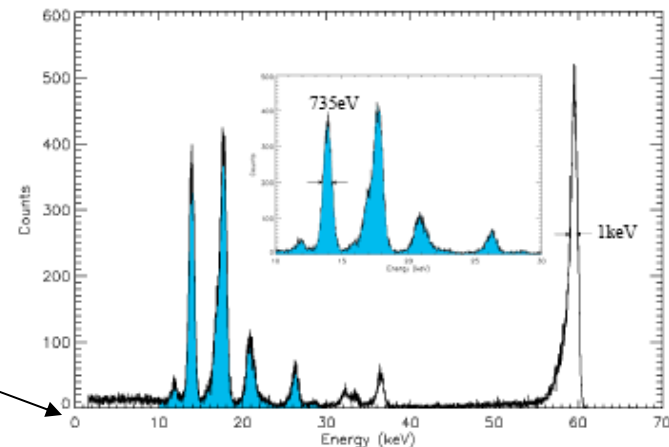
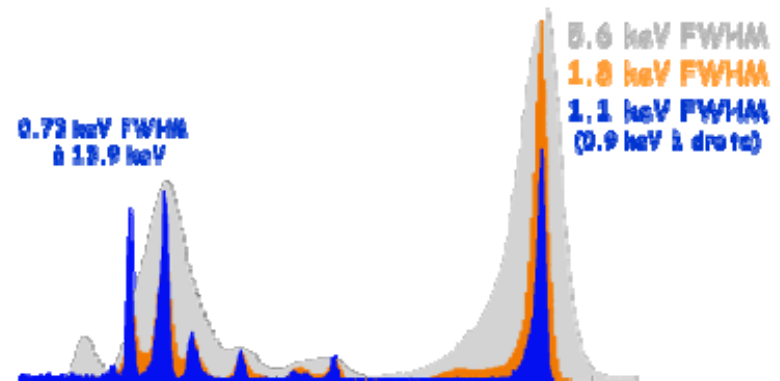


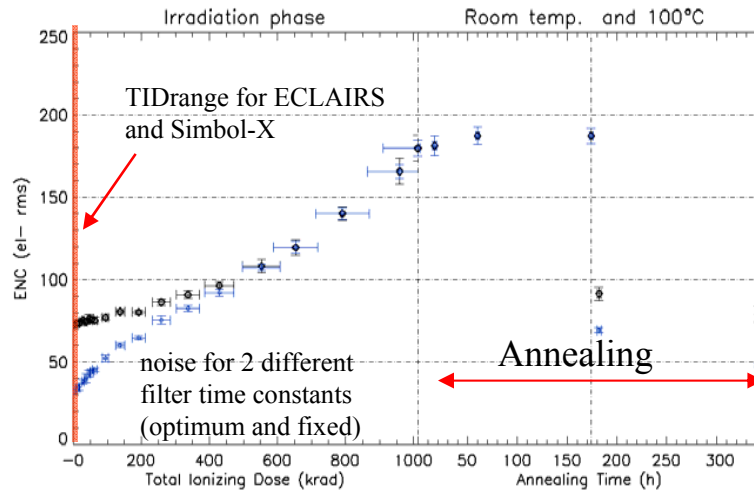
Fig. 6. Spectrum of an ^{241}Am source obtained with a $4.1 \times 4.1 \times 0.5 \text{ mm}^3$ CdTe detector equipped with a Schottky contact at the anode. The cathode is $2 \times 2 \text{ mm}^2$ pixel surrounded by a 1 mm guard ring. The detector is biased under 330 V at 22°C and is connected to the channel #8 of IDef-X V1.0 at a $6\mu\text{s}$ peaking time. The best spectrum is obtained at the highest peaking time because of the very low leakage current of the detector.

IDeF-X family : radiation hardness.



■ IDeF-X V1.0

- TID: Irradiation with 60Co @ 500rad/h up to 1 Mrad

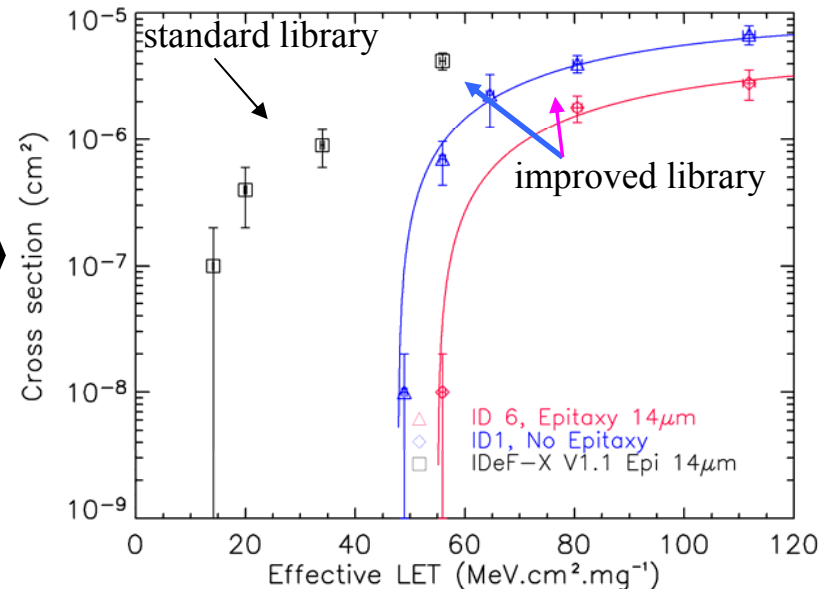


- Up to 1 Mrad: no visible effect excepted on noise performances => Noise increase cleared by annealing.

For ECLAIRs and SIMBOL-X

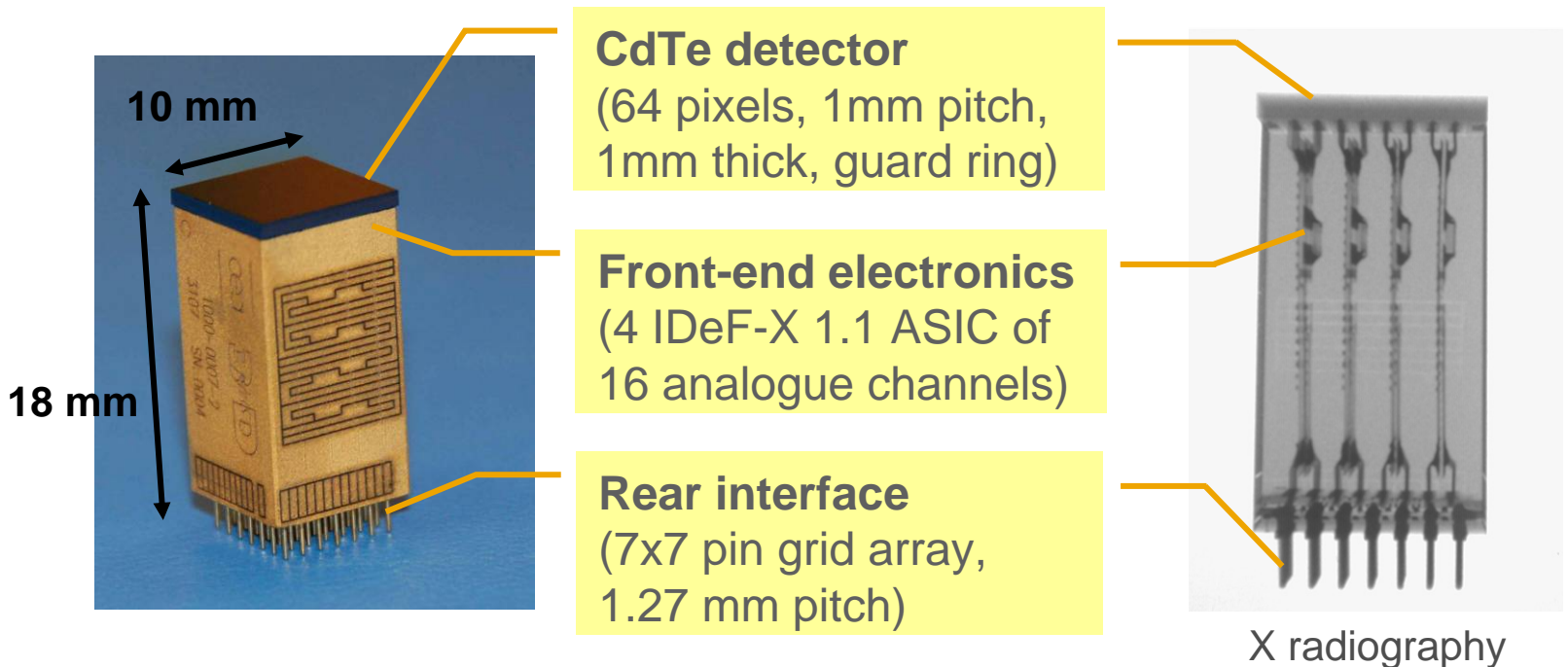
New digital library to improve hardness against SEL:

Test on Idef-X V2.E => no anti latchup circuit required for the ECLAIRs mission.



CALISTE 64 : 3D Xray microcamera for SIMBOL-X

- A hybrid component based on a 3D Plus space proof technology.



- Four micro PCB perpendicular to detection plan.
- Four ASICs to read out 2 rows of eight pixels each.
- Lateral routing to share signals between ASICs.

3D technology

©A. Klumpp (IZM)

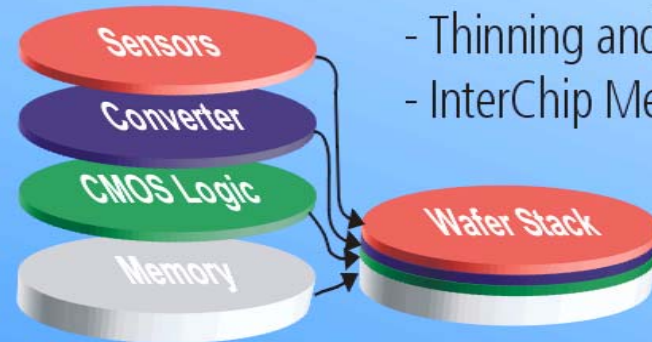
- Increasing integration density, mixing technologies
- Wafer thinning to $<50 \mu\text{m}$
- Minimization of interconnects
- Large industrial demand
 - Processors, image sensors...



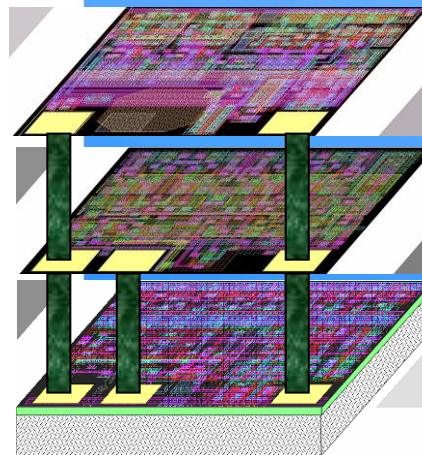
sept 2008

C. de La Taille

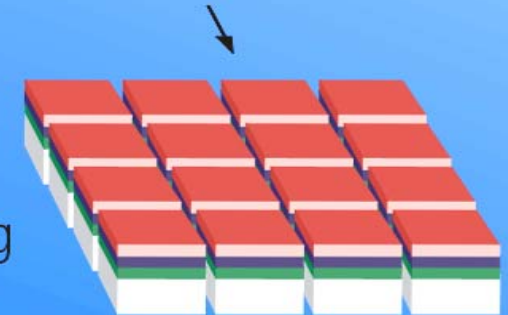
Wafer-to-Wafer



- Planar IC Technologies
- Thinning and Bonding
- InterChip Metallization



ing

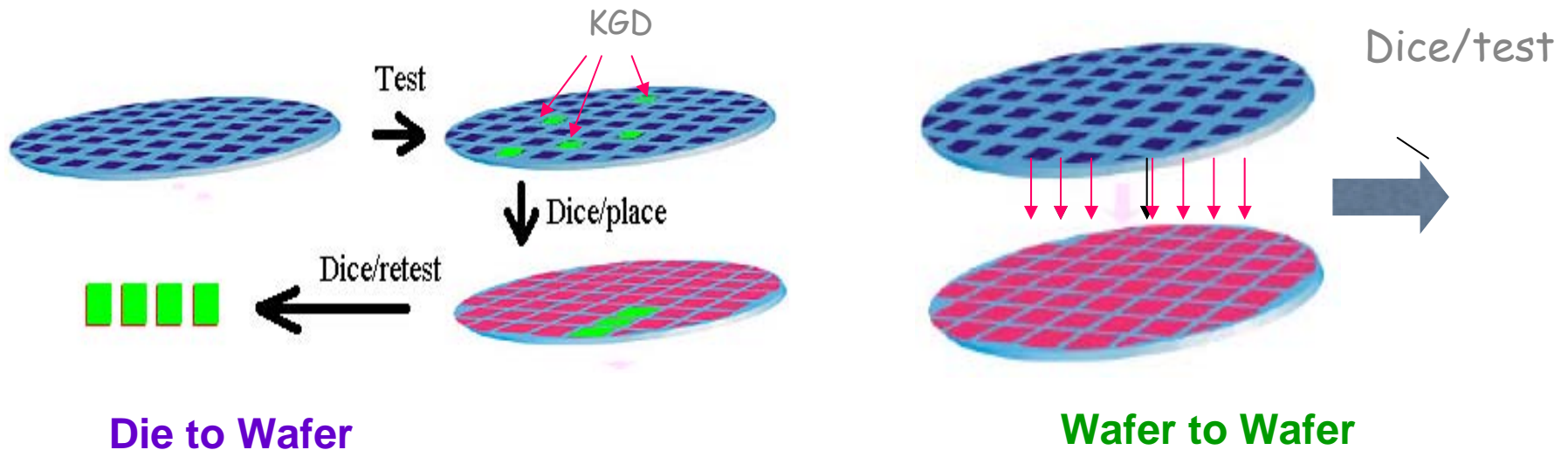


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3D technologies

■ Wafer stacking



Die to Wafer bonding

- Permits use of different size Wafers
- Lends itself to using KGD (Known Good Die) for higher yields

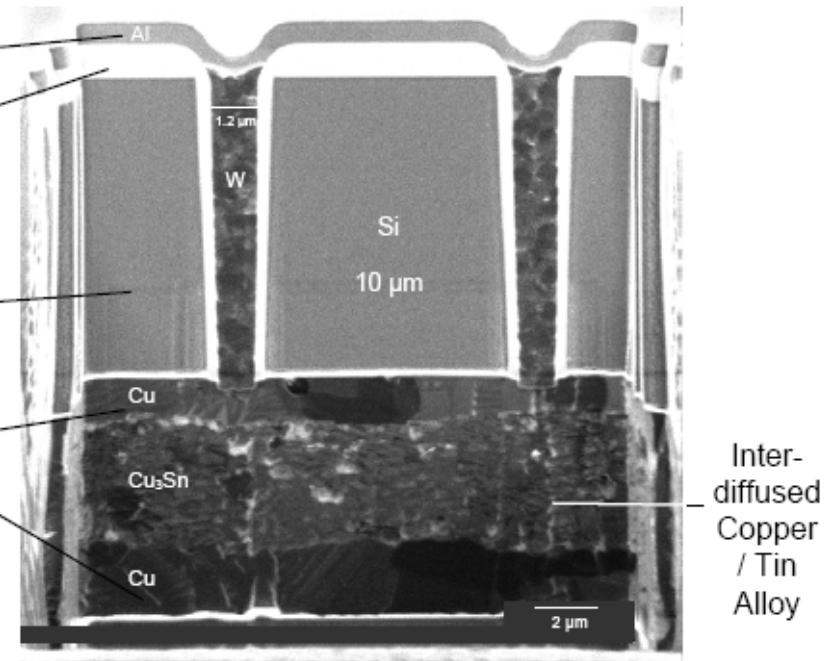
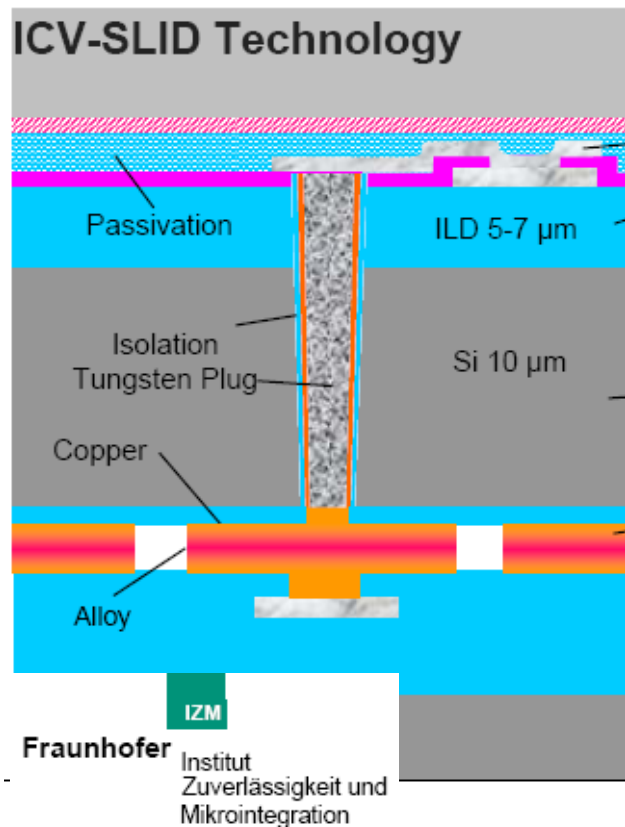
Wafer to Wafer bonding

- - must have same size wafers
- - Less material handling but lower overall yield

ICV : Inter-Chip vias

- Processes « via first » and « via last »
- Diameters : 1 μm to 50 μm
- Aspect ratio ~ 10

- Hole etching and chip thinning
- Via formation with W-plugs.
- Face to face or die up connections.
- 2.5 Ohm/per via (including SLID).



Conclusion

- A real move towards “smart sensors”
- micro-electronics getting closer to detector
 - Unavoidable with increase of channels number
 - Cost reduction
- Backend more and more integrated
 - Integration of ADC
 - Signal processing
 - Loading of parameters
- Coming up : 3D integration
- 4-side abutable sensors

